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(54) **Projection system with a polarization-modulating element having a variable thickness profile**  
Projektionssystem mit einem polarisationsmodulierenden optischen Element mit variabler Dicke  
Système de projection avec un élément optique de modulation de la polarisation ayant une épaisseur variable

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- (56) References cited:  
**GB-A- 856 621 US-A- 3 630 598**  
**US-A- 5 867 315**

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**Description****BACKGROUND OF THE INVENTION**

5 **[0001]** The invention relates to an optical element that affects the polarization of light rays. The optical element has a thickness profile and consists or comprises of an optically active crystal with an optical axis.

**[0002]** In the continuing effort to achieve structures of finer resolution in the field of microlithography, there is a parallel pursuit of substantially three guiding concepts. The first of these is to provide projection objectives of very high numerical aperture. Second is the constant trend towards shorter wavelengths, for example 248 nm, 193 nm, or 157 nm. Finally, there is the concept of increasing the achievable resolution by introducing an immersion medium of a high refractive index into the space between the last optical element of the projection objective and the light-sensitive substrate. The latter technique is referred to as immersion lithography.

10 **[0003]** In an optical system that is illuminated with light of a defined polarization, the s- and p-component of the electrical field vector, in accordance with Fresnel's equations, are subject to respectively different degrees of reflection and refraction at the interface of two media with different refractive indices. In this context and hereinafter, the polarization component that oscillates parallel to the plane of incidence of a light ray is referred to as p-component, while the polarization component that oscillates perpendicular to the plane of incidence of a light ray is referred to as s-component. The different degrees of reflection and refraction that occur in the s-component in comparison to the p-component have a significant detrimental effect on the imaging process.

15 **[0004]** This problem can be avoided with a special distribution of the polarization where the planes of oscillation of the electrical field vectors of individual linearly polarized light rays in a pupil plane of the optical system have an approximately radial orientation relative to the optical axis. A polarization distribution of this kind will hereinafter be referred to as radial polarization. If a bundle of light rays that are radially polarized in accordance with the foregoing definition meets an interface between two media of different refractive indices in a field plane of an objective, only the p-component of the electrical field vector will be present, so that the aforementioned detrimental effect on the imaging quality is reduced considerably.

20 **[0005]** In analogy to the foregoing concept, one could also choose a polarization distribution where the planes of oscillation of the electrical field vectors of individual linearly polarized light rays in a pupil plane of the system have an orientation that is perpendicular to the radius originating from the optical axis. A polarization distribution of this type will hereinafter be referred to as tangential polarization. If a bundle of light rays that are tangentially polarized in accordance with this definition meets an interface between two media of different refractive indices, only the s-component of the electrical field vector will be present so that, as in the preceding case, there will be uniformity in the reflection and refraction occurring in a field plane.

25 **[0006]** Providing an illumination with either tangential or radial polarization in a pupil plane is of high importance in particular when putting the aforementioned concept of immersion lithography into practice, because of the considerable negative effects on the state of polarization that are to be expected based on the differences in the refractive index and the strongly oblique angles of incidence at the respective interfaces from the last optical element of the projection objective to the immersion medium and from the immersion medium to the coated light-sensitive substrate.

30 **[0007]** U.S. Patent 6,191,880 B1 discloses an optical arrangement for generating an approximately radial polarization. The arrangement includes among other things a raster of half-wave plates whose respective directions of preference are oriented so that when linearly polarized light passes through the raster arrangement, the plane of oscillation is rotated into the direction of a radius originating from the optical axis. However, because the raster arrangement is produced by joining a large number of individually oriented half-wave plates, it is expensive to produce. Furthermore, the change in the direction of the polarization is constant within the area of each individual half-wave plate whose diameter is typically between 10 and 20 mm, so that no continuous radial polarization can be produced through this concept.

35 **[0008]** A birefringent element of crystalline quartz with an irregularly varying thickness is proposed in DE 198 07 120 A1 for the compensation of local aberrations of a defined state of polarization in an optical system. However, the variation in thickness in a birefringent element of this type leads to locally different states of polarization. In particular, the linear state of polarization is, as a rule, not preserved in an arrangement of this type.

40 **[0009]** Another polarization-modulating element having a variable thickness is known from publication GB 856 621 A while publication US 2003/095241 A1 proposes a lithographic projection system.

**OBJECT OF THE INVENTION**

45 **[0010]** The present invention therefore has the objective to propose a polarization-modulating optical element which - with a minimum loss of intensity - affects the polarization of light rays in such a way that from linearly polarized light with a first distribution of the directions of the oscillation planes of individual light rays, the optical element generates linearly polarized light with a second distribution of the directions of the oscillation planes of individual light rays.

**[0011]** Further objects of the present invention are to propose an optical system with improved properties of the polarization-modulating optical element regarding thermal stability of the second distribution of oscillation planes (polarization distribution), and to minimize the influence of additional optical elements in the optical system to the polarization distribution after the light rays have passed these elements.

## SUMMARY OF THE INVENTION

**[0012]** To meet the foregoing objectives, a projection system is specified in the independent claims. Additional preferred embodiments of the optical projection systems according to the present invention are given in the dependent claims.

**[0013]** A projection system comprising a polarization-modulating optical element according to the invention has the effect that the plane of oscillation of a first linearly polarized light ray and the plane of oscillation of a second linearly polarized light ray are rotated, respectively, by a first and a second angle of rotation, with the first angle of rotation being different from the second angle of rotation. According to the invention, the polarization-modulating optical element is made of an optically active material, the axis of which being parallel to the optical axis of the projection system.

**[0014]** Advantageous further developments of the inventive concept are described hereinafter.

**[0015]** In order to generate from linearly polarized light an arbitrarily selected distribution of linearly polarized light rays with a minimum loss of intensity, an optically active crystal with an optical axis is used as raw material for the polarization-modulating optical element. The optical axis of a crystal, also referred to as axis of isotropy, is defined by the property that there is only one velocity of light propagation associated with the direction of the optical axis. In other words, a light ray traveling in the direction of an optical axis is not subject to a linear birefringence. The polarization-modulating optical element has a thickness profile that varies in the directions perpendicular to the optical axis of the crystal. The term "linear polarization distribution" in this context and hereinafter is used with the meaning of a polarization distribution in which the individual light rays are linearly polarized but the oscillation planes of the individual electrical field vectors can be oriented in different directions.

**[0016]** If linearly polarized light traverses the polarization-modulating optical element along the optical axis of the crystal, the oscillation plane of the electrical field vector is rotated by an angle that is proportional to the distance traveled inside the crystal. The sense of rotation, i.e., whether the oscillation plane is rotated clockwise or counterclockwise, depends on the crystal material, for example right-handed quartz vs. left-handed quartz. The polarization plane is parallel to the respective directions of the polarization and the propagation of the light ray. In order to produce an arbitrarily selected distribution of the angles of rotation, it is advantageous if the thickness profile is designed so that the plane of oscillation of a first linearly polarized light ray and the plane of oscillation of a second linearly polarized light ray are rotated, respectively, by a first and a second angle of rotation, with the first angle of rotation being different from the second angle of rotation. By shaping the element with a specific thickness at each location, it is possible to realize arbitrarily selected angles of rotation for the oscillation planes.

**[0017]** Different optically active materials have been found suitable dependent on the wavelength of the radiation being used, specifically quartz,  $\text{TeO}_2$ , and  $\text{AgGaS}_2$ .

**[0018]** In an advantageous embodiment of the invention, the polarization-modulating optical element has an element axis oriented in the same direction as the optical axis of the crystal. In relation to the element axis, the thickness profile of the optical element is a function of the azimuth angle  $\theta$  alone, with the azimuth angle  $\theta$  being measured relative to a reference axis that intersects the element axis at a right angle. With a thickness profile according to this design, the thickness of the optical element is constant along a radius that intersects the element axis at a right angle and forms an azimuth angle  $\theta$  with the reference axis.

**[0019]** In a further advantageous embodiment of the invention, an azimuthal section  $d(r=\text{const.}, \theta)$  of the thickness profile  $d(r, \theta)$  at a constant distance  $r$  from the element axis is a linear function of the azimuth angle  $\theta$ . In the ideal case, this azimuthal section has a discontinuity at the azimuth angle  $\theta=0$ . The linear function  $d(r=\text{const.}, \theta)$  at a constant distance

$r$  from the element axis has a slope  $|m| = \frac{180^\circ}{\alpha \pi r}$ , wherein  $\alpha$  stands for the specific rotation of the optically active

crystal. At the discontinuity location for  $\theta=0$ , there is an abrupt step in the thickness by an amount of  $360^\circ/\alpha$ . The step at the discontinuity location can also be distributed over an azimuth angle range of a few degrees. However, this has the result of a non-optimized polarization distribution in the transition range.

**[0020]** In a further advantageous embodiment of the invention, an azimuthal section  $d(r=\text{const.}, \theta)$  of the thickness profile  $d(r, \theta)$  at a constant distance  $r$  from the element axis is a linear function of the azimuth angle  $\theta$  with the same slope  $m$  but, in the ideal case, with two discontinuities at the azimuth angles  $\theta=0$  and  $\theta=180^\circ$ , respectively. At each discontinuity location, there is an abrupt step in the thickness by an amount of  $180^\circ/\alpha$ . The two abrupt steps at the discontinuity locations can also be distributed over an azimuth angle range of a few degrees. However, this has the result of a non-optimized polarization distribution in the transition range.

**[0021]** In a further advantageous embodiment of the invention, an azimuthal section  $d(r=\text{const.},\theta)$  of the thickness profile  $d(r,\theta)$  at a constant distance  $r$  from the element axis and in a first azimuth angle range of  $10^\circ < \theta < 170^\circ$  is a linear function of the azimuth angle  $\theta$  with a first slope  $m$ , while in a second azimuth angle range of  $190^\circ < \theta < 350^\circ$ , the azimuthal section is a linear function of the azimuth angle  $\theta$  with a second slope  $n$ . The slopes  $m$  and  $n$  have the same absolute magnitude but opposite signs. The magnitude of the slopes  $m$  and  $n$  at a distance  $r$  from the element axis is

$$|m| = |n| = \frac{180^\circ}{\alpha \pi r} .$$

With this arrangement, the thickness profile for all azimuth angles, including  $\theta=0$  and  $\theta=180^\circ$ , is

a continuous function without abrupt changes in thickness.

**[0022]** In a further advantageous embodiment of the invention, the polarization-modulating optical element is divided into a large number of planar-parallel portions of different thickness or comprises at least two planar-parallel portions. These portions can for example be configured as sectors of a circle, but they could also have a hexagonal, square, rectangular, or trapezoidal shape.

**[0023]** In a further advantageous embodiment of the invention, a pair of first plan-parallel portions are arranged on opposite sides of a central element axis of said polarization-modulating optical element, and a pair of second plan-parallel portions are arranged on opposite sides of said element axis and circumferentially displaced around said element axis with respect to said first plan-parallel portions, wherein each of said first portions has a thickness being different from a thickness of each of said second portions.

**[0024]** In a further advantageous embodiment of the invention, a plane of oscillation of linearly polarized light passing through the polarization-modulating optical element is rotated by a first angle of rotation  $\beta_1$  within at least one of said first plan-parallel portions and by a second angle of rotation  $\beta_2$  within at least one of said second plan-parallel portions, such that  $\beta_1$  and  $\beta_2$  are approximately conforming or conform to the expression  $|\beta_2 - \beta_1| = (2n+1) \cdot 90^\circ$ , with  $n$  representing an integer.

**[0025]** In an advantageous embodiment,  $\beta_1$  and  $\beta_2$  are approximately conforming or conform to the expressions  $\beta_1 = 90^\circ + p \cdot 180^\circ$ , with  $p$  representing an integer, and  $\beta_2 = q \cdot 180^\circ$ , with  $q$  representing an integer other than zero. As will be discussed below in more detail, such an embodiment of the polarization modulating optical element may be advantageously used in affecting the polarization of traversing polarized light such that exiting light has a polarization distribution being -depending of the incoming light- either approximately tangentially or approximately radially polarized.

**[0026]** The pair of second plan-parallel portions may particularly be circumferentially displaced around said element axis with respect to said pair of first plan-parallel portions by approximately  $90^\circ$ .

**[0027]** In a further advantageous embodiment of the invention, said pair of first plan-parallel portions and said pair of second plan-parallel portions are arranged on opposite sides of a central opening or a central obscuration of said polarization-modulating optical element.

**[0028]** Adjacent portions of said first and second pairs can be spaced apart from each other by regions being opaque to linearly polarized light entering said polarization-modulating optical element. Said portions of said first and second group can particularly be held together by a mounting. Said mounting can be opaque to linearly polarized light entering said polarization-modulating optical element. The mounting can have a substantially spoke-wheel shape.

**[0029]** In a further advantageous embodiment of the invention, the polarization-modulating optical element comprises a first group of substantially planar-parallel portions wherein a plane of oscillation of traversing linearly polarized light is rotated by a first angle of rotation  $\beta_1$ , and a second group of substantially planar-parallel portions wherein a plane of oscillation of traversing linearly polarized light is rotated by a second angle of rotation, such that  $\beta_1$  and  $\beta_2$  are approximately conforming or conform to the expression  $|\beta_2 - \beta_1| = (2n+1) \cdot 90^\circ$ , with  $n$  representing an integer.

**[0030]** In a further advantageous embodiment of the invention,  $\beta_1$  and  $\beta_2$  are approximately conforming to the expressions  $\beta_1 = 90^\circ + p \cdot 180^\circ$ , with  $p$  representing an integer, and  $\beta_2 = q \cdot 180^\circ$ , with  $q$  representing an integer other than zero.

**[0031]** In a further advantageous embodiment of the invention, the thickness profile of the polarization-modulating optical element has a continuous surface contour without abrupt changes in thickness, whereby an arbitrarily selected polarization distribution can be generated whose thickness profile is represented by a continuous function of the location.

**[0032]** To ensure an adequate mechanical stability of the optical element, it is important to make the minimal thickness  $d_{\min}$  of the polarization-modulating optical element at least equal to 0.002 times the element diameter  $D$ .

**[0033]** If the optically active material used for the optical element also has birefringent properties as is the case for example with crystalline quartz, the birefringence has to be taken into account for light rays whose direction of propagation deviates from the direction of the optical crystal axis. A travel distance of  $90^\circ/\alpha$  inside the crystal causes a linear polarization to be rotated by  $90^\circ$ . If birefringence is present in addition to the rotating effect, the  $90^\circ$  rotation will be equivalent to an exchange between the fast and slow axis in relation to the electrical field vector of the light. Thus, a total compensation of the birefringence is provided for light rays with small angles of incidence if the distance traveled inside the crystal equals an integer multiple of  $180^\circ/\alpha$ . In order to meet the aforementioned requirement for mechanical stability while simultaneously minimizing the effects of birefringence, it is of particular advantage if the polarization-modulating optical

element is designed with a minimum thickness of  $d_{\min} = N \cdot \frac{90^\circ}{\alpha}$ , where N represents a positive integer.

**[0034]** From a manufacturing point of view, it is particularly advantageous to provide the optical element with a hole at the center or with a central obscuration.

**[0035]** For light rays propagating not exactly parallel to the optical crystal axis, there will be deviations of the angle of rotation. In addition, the birefringence phenomenon will have an effect. It is therefore particularly advantageous if the maximum angle of incidence of an incident light bundle with a large number of light rays within a spread of angles relative to the optical crystal axis is no larger than 100 mrad, preferably no larger than 70 mrad, and with special preference no larger than 45 mrad.

**[0036]** In order to provide an even more flexible control over a state of polarization, an optical arrangement is advantageously equipped with a device that allows at least one further polarization-modulating optical element to be placed in the light path. This further polarization-modulating optical element can be an additional element with the features described above. However, it could also be configured as a planar-parallel plate of an optically active material or an arrangement of two half-wavelength plates whose respective fast and slow axes of birefringence are rotated by 45° relative to each other.

**[0037]** The further polarization-modulating optical element that can be placed in the optical arrangement can in particular be designed in such a way that it rotates the oscillation plane of a linearly polarized light ray by 90°. This is particularly advantageous if the first polarization-modulating element in the optical arrangement produces a tangential polarization. By inserting the 90°-rotator, the tangential polarization can be converted to a radial polarization.

**[0038]** In a further embodiment of the optical arrangement, it can be advantageous to configure the further polarization-modulating optical element as a planar-parallel plate which works as a half-wavelength plate for a half-space that corresponds to an azimuth-angle range of 180°. This configuration is of particular interest if the first polarization-modulating optical element has a thickness profile ( $r = \text{const.}, \theta$ ) that varies only with the azimuth angle  $\theta$  and if, in a first azimuth angle range of  $10^\circ < \theta < 170^\circ$ , the thickness profile ( $r = \text{const.}, \theta$ ) is a linear function of the azimuth angle  $\theta$  with a first slope m, while in a second azimuth angle range of  $190^\circ < \theta < 350^\circ$ , the thickness profile is a linear function of the azimuth angle  $\theta$  with a second slope n, with the slopes m and n having the same absolute magnitude but opposite signs.

**[0039]** The refraction occurring in particular at sloped surfaces of a polarization-modulating element can cause a deviation in the direction of an originally axis-parallel light ray after it has passed through the polarization-modulating element. In order to compensate this type of deviation of the wave front which is caused by the polarization-modulating element, it is advantageous to arrange a compensation plate of a not optically active material in the light path of an optical system, with a thickness profile of the compensation plate designed so that it substantially compensates an angular deviation of the transmitted radiation that is caused by the polarization-modulating optical element. Alternatively, an immersion fluid covering the profiled surface of the polarization-modulating element could be used for the same purpose.

**[0040]** Polarization-modulating elements of the foregoing description, and optical arrangements equipped with them, are advantageously used in projection systems for microlithography applications. In particular, polarization-modulating elements of this kind and optical arrangements equipped with them are well suited for projection systems in which the aforementioned immersion technique is used, i.e., where an immersion medium with a refractive index different from air is present in the space between the optical element nearest to the substrate and the substrate.

#### BRIEF DESCRIPTION OF THE DRAWINGS

**[0041]** The invention will hereinafter be explained in more detail with reference to the attached drawings, wherein:

Figure 1 illustrates a polarization-modulating optical element with a thickness profile;

Figure 2 schematically illustrates how the plane of oscillation is rotated when a linearly polarized light ray propagates along the optical axis in an optically active crystal;

Figure 3 illustrates a first exemplary embodiment of a polarization-modulating optical element;

Figure 4a schematically illustrates a second exemplary embodiment of a polarization-modulating optical element;

Figure 4b illustrates, the thickness profile as a function of the azimuth angle in the embodiment of the polarization-modulating optical element of Figure 4a;

- Figure 4c illustrates the thickness profile as a function of the azimuth angle in a further embodiment of the polarization-modulating optical element;
- 5 Figure 4d illustrates the thickness profile as a function of the azimuth angle in the embodiment of the polarization-modulating optical element of Figure 3;
- Figure 4e illustrates the thickness profile as a function of the azimuth angle in a further embodiment of the polarization-modulating optical element;
- 10 Figure 4f schematically illustrates a further exemplary embodiment of a polarization-modulating optical element;
- Figure 5 schematically illustrates the polarization distribution of a bundle of light rays before and after passing through the polarization-modulating optical element with the thickness profile according to Figure 3 or 4d;
- 15 Figure 6 schematically illustrates the polarization distribution of a bundle of light rays before and after passing through an optical arrangement with the polarization-modulating optical element with the thickness profile according to Figure 3 and a further polarization-modulating optical element;
- Figure 7a schematically illustrates the polarization distribution of a bundle of light rays before and after passing through an optical arrangement with the polarization-modulating optical element with the thickness profile according to Figure 4e and a planar-parallel plate, one half of which is configured as a half-wave plate;
- 20 Figure 7b shows a plan view of a planar-parallel plate, one half of which is configured as a half-wave plate;
- 25 Figure 8 schematically illustrates a microlithography projection system with a polarization-modulating optical element; and
- Figure 9 schematically shows a parallel plane plate of optical active material used as a polarization-modulating element by adjusting its temperature and/or temperature profile;
- 30 Figure 10 shows a combination of a parallel plate of optical active material with a plate made of birefringent material; and
- Figure 11 shows schematically a temperature compensated polarization-modulating optical element for the application in an optical system.
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#### PROVISIONAL DESCRIPTION OF PREFERRED EMBODIMENTS

40 **[0042]** Figure 1 illustrates a polarization-modulating optical element 1 of an optically active material. Particularly well suited for this purpose are optically active crystals with at least one optical crystal axis which are transparent for the wavelength of the light being used. For example  $\text{TeO}_2$  works in a range of wavelengths from 1000 nm down to 300 nm,  $\text{AgGaS}_2$  works from 500 nm to 480 nm, and quartz from 800 nm down to 193 nm. The polarization-modulating optical element 1 is designed so that the element axis is oriented parallel to the optical crystal axis. In order to produce a selected polarization distribution, the optical element 1 is designed with a thickness profile (measured parallel to the element axis EA) which varies in the directions perpendicular to the element axis EA, also comprising variations in thickness of the optical element in an azimuth direction  $\theta$  (see Fig. 3) at e.g. a fixed distance of the element axis EA.

45 **[0043]** Figure 2 will serve to explain the function of optically active crystals, and in particular of polarization-modulating elements made from such crystals, in more detail.

50 **[0044]** Optically active crystals have at least one optical axis OA which is inherent in the crystal structure. When linearly polarized light travels along this optical axis OA, the plane of oscillation of the electrical field vector 206 is rotated by an angle  $\beta$  of proportionate magnitude as the distance  $d$  traveled by the light inside the crystal 202. The proportionality factor between distance  $d$  and angle of rotation is the specific rotation  $\alpha$ . The latter is a material-specific quantity and is dependent on the wavelength of the light rays propagating through the crystal. For example in quartz, the specific rotation at a wavelength of 180 nm was measured as about  $\alpha = (325.2 \pm 0.5)^\circ/\text{mm}$ , at 193 nm  $\alpha = 323.1^\circ/\text{mm}$  at a temperature of 21.6 °C.

55 **[0045]** It is also important for the present invention, applying optically active materials in an illumination system and/or an objective of a projection optical system of e.g. a projection apparatus used in microlithography, that also the temperature dependency of the specific rotation is considered. The temperature dependency of the specific rotation  $\alpha$  for a given

wavelength is to a good and first linear approximation given by  $\alpha(T) = \alpha_0(T_0) + \gamma(T - T_0)$ , where  $\gamma$  is the linear temperature coefficient of the specific rotation  $\alpha$ . In this case  $\alpha(T)$  is the optical activity coefficient or specific rotation at the temperature  $T$  and  $\alpha_0$  is the specific rotation at a reference temperature  $T_0$ . For optical active quartz material the value  $\gamma$  at a wavelength of 193 nm and at room temperature is  $\gamma = 2.36 \text{ mrad}/(\text{mm} \cdot \text{K})$ .

**[0046]** Referring again to Fig. 2, in particular, light that propagates inside the crystal 202 along the optical axis OA is not subject to a linear birefringence. Thus, when a linearly polarized light ray traverses an optically active crystal 202 along the optical axis OA, its state of polarization remains the same except for the change in the spatial orientation of the plane of oscillation of the electrical field vector 206 which depends on the distance  $d$  traveled by the light ray inside the crystal 202.

**[0047]** Based on this property of an optically active crystal, it is possible to produce an arbitrarily selected linear polarization distribution by designing the polarization-modulating optical element 1 of Figure 1 with a thickness profile that varies dependent on the location. The thickness profile is designed to have the effect that the directions of polarization of parallel linearly polarized light rays are rotated by an angle that varies dependent on the location where the light ray traverses the optical element.

**[0048]** More general, alternative or in addition to the variation of the thickness  $d = d(x, y)$  of the polarization-modulating element, the specific rotation  $\alpha$  may itself be dependent on the location within the modulating element such that  $\alpha$  becomes an  $\alpha(x, y, z)$  or  $\alpha(r, \theta, z)$ , where  $x, y$  or  $r, \theta$  are Cartesian or polar coordinates in a plane perpendicular to the element axis EA (or alternative to the optical axis OA) of the polarization-modulating element, as shown e.g. in Fig. 1, where  $z$  is the axis along the element axis EA. Of course also a description in spherical-coordinates like  $r, \theta, \phi$ , or others is possible. Taking into account the variation of the specific rotation  $\alpha$ , the polarization-modulating optical element in general comprises a varying profile of the "optical effective thickness  $D$ " defined as  $D(x, y) = d(x, y) \cdot \alpha(x, y)$ , if there is no dependency of  $\alpha$  in  $z$ -direction. In the case that  $\alpha$  may also depend on the  $z$ -direction (along the optical axis or element axis EA, or more general along a preferred direction in an optical system or a direction parallel to the optical axis of an optical system)  $D$  has to be calculated by integration  $D(x, y) = \int \alpha(x, y, z) dz(x, y)$ , along the polarization-modulating optical element. In general, if a polarization-modulating optical element is used in an optical system, having an optical axis or a preferred direction defined by the propagation of a light beam through the optical system, the optical effective thickness  $D$  is calculated by integrating the specific rotation  $\alpha$  along the light path of a light ray within the polarization-modulating optical element. Under this general aspect the present invention relates to an optical system comprising an optical axis or a preferred direction given by the direction of a light beam propagating through the optical system. The optical system also comprises a polarization-modulating optical element described by coordinates of a coordinate system, wherein one preferred coordinate of the coordinate system is parallel to the optical axis of the optical system or parallel to the preferred direction. As an example, in the above case this preferred direction was the  $z$ -coordinate which is the preferred coordinate. Additionally the polarization-modulating optical element comprises optical active material and also a profile of effective optical thickness  $D$  as defined above, wherein the effective optical thickness  $D$  varies at least as a function of one coordinate different from the preferred coordinate of the coordinate system describing the polarization-modulating optical element. In the above example the effective optical thickness  $D$  varies at least as a function of the  $x$ - or  $y$ -coordinate, different from the  $z$ -coordinate (the preferred coordinate). There are different independent methods to vary the effective optical thickness of an optical active material. One is to vary the specific rotation by a selection of appropriate materials, or by subjecting the optically active material to a non-uniform temperature distribution, or by varying the geometrical thickness of the optically active material. Also combinations of the mentioned independent methods result in a variation of the effective optical thickness of an optical active material.

**[0049]** Figure 3 illustrates an embodiment of the polarization-modulating optical element 301 which is suited specifically for producing a tangential polarization. A detailed description will be presented in the context of Figures 4d and 5. The embodiment illustrated in Figure 3 will serve to introduce several technical terms that will be used hereinafter with the specific meanings defined here.

**[0050]** The polarization-modulating optical element 301 has a cylindrical shape with a base surface 303 and an opposite surface 305. The base surface 303 is designed as a planar circular surface. The element axis EA extends perpendicular to the planar surface. The opposite surface 305 has a contour shape in relation to the element axis EA in accordance with a given thickness profile. The optical axis of the optically active crystal runs parallel to the element axis EA. The reference axis RA, which extends in the base plane, intersects the element axis at a right angle and serves as the reference from which the azimuth angle  $\theta$  is measured. In the special configuration illustrated in Figure 3, the thickness of the polarization-modulating optical element 301 is constant along a radius  $R$  that is perpendicular to the element axis EA and directed at an angle  $\theta$  relative to the reference axis RA. Thus, the thickness profile in the illustrated embodiment of Figure 3 depends only on the azimuth angle  $\theta$  and is given by  $d = d(\theta)$ . The optical element 301 has an optional central bore 307 coaxial with the element axis EA. In an other preferred embodiment of the polarization-optical element the thickness may vary along the radius  $R$  such that the thickness profile is  $d = d(R, \theta)$ . In a further more generalized preferred embodiment the thickness profile shown in Fig. 3 is not representing the geometrical thickness  $d$  of the polarization-optical element, as described above, but the profile represents the optical effective thickness  $D = D(R, \theta) = D(x,$

y), depending on the used coordinate system. In this case also any profile of the specific rotation like e.g.  $\alpha = \alpha(x,y) = \alpha(R,\theta)$  or  $\alpha = \alpha(x,y,z) = \alpha(R,\theta,z)$  is considered in the profile of the polarization-modulating optical element which is effective for a change in the direction of the polarization plane of a passed light beam.

**[0051]** In addition it should be mentioned that the polarization-modulating optical element 301 not necessary need to comprise a planar base surface 303. This surface in general can also comprise a contour shaped surface e.g. similar or equal to the surface as designated by 305 shown in Fig. 3. In such a case it is of advantage to describe the contour surfaces 303 and 305 relative to a plane surface perpendicular to the optical axis or element axis.

**[0052]** Figure 4a schematically illustrates a further embodiment of the polarization-modulating optical element 401. The element axis EA through the center of the polarization-modulating optical element 401 in this representation runs perpendicular to the plane of the drawing, and the optical crystal axis of the crystal runs parallel to the element axis. Like the embodiment of Figure 3, the polarization-modulating optical element 401 has an optional central bore 407. The polarization-modulating optical element 401 is divided into a large number of planar-parallel portions 409 in the shape of sectors of a circle which differ in their respective thicknesses. Alternative embodiments with different shapes of the portions 409 are conceivable. They could be configured, e.g., as hexagonal, square, rectangular or trapeze-shaped raster elements.

**[0053]** As described in connection with Fig. 3, the embodiment according to Fig. 4 a can be modified such that the different thicknesses of the sectors should be understood as different effective optical thicknesses D. In this case the specific rotation  $\alpha$  may vary from one segment to the other too. To manufacture such an embodiment, the polarization-modulating optical element can e.g. have a shape as shown in Fig. 4a in which the sectors 409 are at least partly exchanged e.g. by any optical inactive material, which is the simplest case to vary the specific rotation  $\alpha$  to zero. Also as a further embodiment the sectors 409 may be replaced by cuvettes or cells which are filled with an optical active or optical inactive liquid. In this case the polarization-modulating optical element may comprise optical active and optical inactive sections. If the sectors 409 are only partly replaced by cuvettes or if at least one cuvette is used in the polarization-modulating optical element 401, a combination of e.g. optical active crystals with e.g. optical active or optical inactive liquids in one element 40 is possible. Such an optical system according to the present invention may comprise a polarization-modulating optical element which comprises an optically active or an optically inactive liquid and/or an optically active crystal. Further, it is advantageously possible that the polarization-modulating optical element of the optical system according to the present invention comprises clockwise and counterclockwise optically active materials. These materials could be solid or liquid optically active materials. Using liquids in cuvettes has the advantage that by changing the liquids, or the concentration of the optical active material within the liquid, the magnitude of the change in polarization can be easily controlled. Also any thermal changes of the specific rotation  $\alpha$  due to the thermal coefficient  $\gamma$  of the specific rotation  $\alpha$  can be controlled e.g. by temperature control of the optical active liquid such that either the temperature is constant within the cuvette, or that the temperate has predefined value T such that the specific rotation will have the values  $\alpha(T) = \alpha_0(T_0) + \gamma^*(T - T_0)$ . Also the formation of a certain temperature distribution within the liquid may be possible with appropriate heating and/or cooling means controlled by control means.

**[0054]** The optical systems in accordance with the present invention advantageously modify respective planes of oscillation of a first linearly polarized light ray and a second linearly polarized light ray. Both light rays propagating through the optical system, and being at least a part of the light beam propagating through the optical system. The light rays are also passing the polarization-modulating optical element with different paths, and are rotated by a respective first and second angle of rotation such that the first angle is different of the second angle. In general the polarization-modulating optical element of the optical systems according to the present invention transform a light bundle with a first linear polarization distribution, which enters said polarization-modulating optical element, into a light bundle exiting said polarization-modulating optical element. The exiting light bundle having a second linear polarization distribution, wherein the second linear polarization distribution is different from the first linear polarization distribution.

**[0055]** Figure 4b shows the thickness profile along an azimuthal section  $d(r=\text{const.},\theta)$  for the polarization-modulating optical element 401 divided into sectors as shown in Figure 4a. The term azimuthal section as used in the present context means a section traversing the thickness profile  $d(\theta,r)$  along the circle 411 marked in Figure 4a, i.e., extending over an azimuth angle range of  $0^\circ \leq \theta \leq 360^\circ$  at a constant radius r. In general the profile shows the optical effective thickness  $D = D(\theta)$  along a circle 411.

**[0056]** An azimuthal section of a polarization-modulating optical element 401 that is divided into sector-shaped portions has a stair-shaped profile in which each step corresponds to the difference in thickness d or optical effective thickness D between neighboring sector elements. The profile has e.g. a maximum thickness  $d_{\text{max}}$  and a minimum thickness  $d_{\text{min}}$ . In order to cover a range of  $0 \leq \beta \leq 360^\circ$  for the range of the angle of rotation of the oscillation plane of linearly polarized light, there has to be a difference of  $360^\circ/\alpha$  between  $d_{\text{max}}$  and  $d_{\text{min}}$ . The height of each individual step of the profile depends on the number n of sector elements and has a magnitude of  $360^\circ/(n \cdot \alpha)$ . At the azimuth angle  $\theta = 0^\circ$ , the profile has a discontinuity where the thickness of the polarization-modulating optical element 401 jumps from  $d_{\text{min}}$  to  $d_{\text{max}}$ . A different embodiment of the optical element can have a thickness profile in which an azimuthal section has two discontinuities of the thickness, for example at  $\theta = 0^\circ$  and  $\theta = 180^\circ$ .

**[0057]** In an alternative embodiment the profile has e.g. a maximum optical effective thickness  $D_{\max}$  and a minimum optical effective thickness  $D_{\min}$ , and the geometrical thickness  $d$  is e.g. constant, resulting in a variation of the specific rotation  $\alpha$  of the individual segments 409 of the element 401. In order to cover a range of  $0 \leq \beta \leq 360^\circ$  for the range of the angle of rotation of the oscillation plane of linearly polarized light, there has to be a difference of  $360^\circ/d$  between  $\alpha_{\max}$  and  $\alpha_{\min}$ . The change of the specific rotation of each individual step of the profile depends on the number  $n$  of sector elements 409 and has a magnitude of  $360^\circ/(n \cdot d)$ . At the azimuth angle  $\theta = 0^\circ$ , the profile has a discontinuity regarding the optical effective thickness where it jumps from  $D_{\min}$  to  $D_{\max}$ . It should be pointed out, that advantageously in this embodiment there is no discontinuity in the geometrical thickness  $d$  of the polarization-modulating element 401. Also the thickness profile of the optical effective thickness in which an azimuthal section has two discontinuities of the optical effective thickness can easily be realized, for example at  $\theta = 0^\circ$  and  $\theta = 180^\circ$ . To realize the defined changes in magnitude of the specific rotation of  $\Delta\alpha = 360^\circ/(n \cdot d)$  (if there are  $n$  angular segments 409 to form the element 401), the individual sector elements 409 are preferably made of or comprises cuvettes or cells, filled with an optical active liquid with the required specific rotation  $\alpha$ . As an example, for the  $m$ -th sector element the specific rotation is  $\alpha(m) = \alpha_{\min} + m \cdot 360^\circ/(n \cdot d)$ , and  $0 \leq m \leq n$ . The required specific rotation e.g. can be adjusted by the concentration of the optical active material of the liquid, or by changing the liquid material itself.

**[0058]** In a further embodiment the segments 409 of a polarization-modulating optical element 401 may comprise components of solid optically active material (like crystalline quartz) and cells or cuvettes filled with optically active material, and these components are placed behind each other in the light propagation direction. Alternative or in addition the cuvette itself may comprise optically active material like crystalline quartz.

**[0059]** The polarization-modulating optical element of the foregoing description converts linearly polarized incident light into a linear polarization distribution in which the oscillation planes of linearly polarized light rays are rotated by an angle that depends on the thickness (or optical effective thickness) of each individual sector element. However, the angle by which the direction of polarization is rotated is constant over an individual sector element. Thus, the distribution function for the directions of the oscillation planes of the individual field vectors takes only certain discrete values.

**[0060]** A continuous distribution of linear polarizations can be achieved with an optical element that has a continuously varying thickness (optical effective thickness) profile along an azimuthal section.

**[0061]** An example of a continuously varying thickness profile is illustrated in Figure 4c. The azimuthal section 411 in this embodiment shows a linear decrease in thickness (in general optical effective thickness) with a slope  $m = -180^\circ/(\alpha \cdot \pi)$  over an azimuth-angle range of  $0 \leq \theta \leq 360^\circ$ . Here the slope is defined as a slope of a screw. Alternatively the slope can be defined by  $m = -180^\circ/(\alpha \cdot \pi \cdot r)$  where  $r$  is the radius of a circle centered at the element axis EA. In this case the slope depends on the distance of the element axis, e.g. if the polarization-modulating optical element 301 has a given constant screw-slope (lead of a screw).

**[0062]** The symbol  $\alpha$  in this context stands for the specific rotation of the optically active crystal. As in the previously described embodiment of Figure 4b, the thickness profile of Figure 4c has likewise a discontinuity at the azimuth angle  $\theta = 0^\circ$ , the thickness of the polarization-modulating optical element 401 jumps from  $d_{\min}$  to  $d_{\max}$  by an amount of approximately  $360^\circ/\alpha$ .

**[0063]** A further embodiment of a polarization-modulating optical element which is shown in Figure 4d has a thickness profile (in general optical effective thickness profile) which is likewise suitable for producing a continuous distribution of linear polarizations, in particular a tangentially oriented polarization. This thickness profile corresponds to the embodiment shown in Figure 3, in which the angle  $\theta$  is measured in counterclockwise direction. The azimuthal section 411 in this embodiment is a linear function of the azimuth angle  $\theta$  with a slope  $m = -180^\circ/(\alpha \cdot \pi)$  over each of two ranges of  $0 < \theta < 180^\circ$  and  $180^\circ < \theta < 360^\circ$ . The thickness profile has discontinuities at  $\theta = 0^\circ$  and  $\theta = 180^\circ$  where the thickness rises abruptly from  $d_{\min}$  to  $d_{\max}$  by an amount of  $180^\circ/\alpha$ .

**[0064]** Figure 4e represents the thickness profile (in general optical effective thickness profile) along an azimuthal section for a further embodiment of the polarization-modulating optical element 401. The azimuthal section is in this case a linear function of the azimuth angle  $\theta$  with a first slope  $m$  for  $0 < \theta < 180^\circ$  and with a second slope  $n$  for  $180^\circ < \theta < 360^\circ$ . The slopes  $m$  and  $n$  are of equal absolute magnitude but have opposite signs. The respective amounts for  $m$  and  $n$  at a distance  $r$  from the element axis are  $m = -180^\circ/(\alpha \cdot \pi \cdot r)$  and  $n = 180^\circ/(\alpha \cdot \pi \cdot r)$ . While the difference between the minimum thickness  $d_{\min}$  and the maximum thickness  $d_{\max}$  is again approximately  $180^\circ/\alpha$ , i.e., the same as in the embodiment of Figure 4d, the concept of using opposite signs for the slope in the two azimuth angle ranges avoids the occurrence of discontinuities.

**[0065]** Additionally it is mentioned that for certain special applications clockwise and counterclockwise optically active materials are combined in a polarization-modulating optical element.

**[0066]** As the slope of the thickness profile along an azimuthal section increases strongly with smaller radii, it is advantageous from a manufacturing point of view to provide a central opening 407 or a central obscuration in a central portion around the central axis of the circular polarization-modulating optical element.

**[0067]** It is furthermore necessary for reasons of mechanical stability to design the polarization-modulating optical element with a minimum thickness  $d_{\min}$  of no less than two thousandths of the element diameter. It is particularly

advantageous to use a minimum thickness of  $d_{\min} = N \cdot 90^\circ / \alpha$ , where N is a positive integer. This design choice serves to minimize the effect of birefringence for rays of an incident light bundle which traverse the polarization-modulating element at an angle relative to the optical axis.

**[0068]** Figure 4f schematically illustrates a further embodiment 421 of the polarization-modulating optical element. As in Figure 4a, the element axis EA through the center of the polarization-modulating optical element 421 runs perpendicular to the plane of the drawing, and the optical crystal axis runs parallel to the element axis. However, in contrast to the embodiments of Figures 3 and 4a where the polarization-modulating optical elements 301, 401 are made preferably of one piece like in the case of crystalline material like crystalline quartz, the polarization-modulating optical element 421 comprises of four separate sector-shaped parts 422, 423, 424, 425 of an optically active crystal material which are held together by a mounting device 426 which can be made, e.g., of metal and whose shape can be described as a circular plate 427 with four radial spokes 428. The mounting is preferably opaque to the radiation which is entering the polarization-modulating optical element, thereby serving also as a spacer which separates the sector-shaped parts 422, 423, 424, 425 from each other. Of course the embodiment of the present invention according to Fig. 4f is not intended to be limited to any specific shape and area of mounting device 426, which may also be omitted.

**[0069]** According to an alternate embodiment not illustrated in Fig. 4f, incident light which is entering the polarization-modulating optical element can also be selectively directed onto the sector-shaped parts, e.g. by means of a diffractive structure or other suitable optical components.

**[0070]** The sector-shaped parts 422 and 424 have a first thickness  $d_1$  which is selected so that the parts 422 and 424 cause the plane of oscillation of linearly polarized axis-parallel light to be rotated by  $90^\circ + p \cdot 180^\circ$ , where p represents an integer. The sector-shaped parts 423 and 425 have a second thickness  $d_2$  which is selected so that the parts 423 and 425 cause the plane of oscillation of linearly polarized axis-parallel light to be rotated by  $q \cdot 180^\circ$ , where q represents an integer other than zero. Thus, when a bundle of axis-parallel light rays that are linearly polarized in the y-direction enters the polarization-modulating optical element 421, the rays that pass through the sector-shaped parts 423 and 425 will exit from the polarization-modulating optical element 421 with their plane of oscillation unchanged, while the rays that pass through the sector-shaped parts 422 and 424 will exit from the polarization-modulating optical element 421 with their plane of oscillation rotated into the x-direction. As a result of passing through the polarization-modulating optical element 421, the exiting light has a polarization distribution which is exactly tangential at the centerlines 429 and 430 of the sector-shaped parts 422, 423, 424, 425 and which approximates a tangential polarization distribution for the rest of the polarization-modulating optical element 421.

**[0071]** When a bundle of axis-parallel light rays that are linearly polarized in the x-direction enters the polarization-modulating optical element 421, the rays that pass through the sector-shaped parts 423 and 425 will exit from the polarization-modulating optical element 421 with their plane of oscillation unchanged, while the rays that pass through the sector-shaped parts 422 and 424 will exit from the polarization-modulating optical element 421 with their plane of oscillation rotated into the y-direction. As a result of passing through the polarization-modulating optical element 421, the exiting light has a polarization distribution which is exactly radial at the centerlines 429 and 430 of the sector-shaped parts 422, 423, 424, 425 and which approximates a radial polarization distribution for the rest of the polarization-modulating optical element 421.

**[0072]** Of course the embodiment of the present invention according to Fig. 4f is not intended to be limited to the shapes and areas and the number of sector-shaped parts exemplarily illustrated in Fig. 4f, so that other suitable shapes (having for example but not limited to trapeze-shaped, rectangular, square, hexagonal or circular geometries) as well as more or less sector-shaped parts 422, 423, 424 and 425 can be used. Furthermore, the angles of rotation  $\beta_1$  and  $\beta_2$  provided by the sector-shaped parts 422, 423, 424, 425 (i.e. the corresponding thicknesses of the sector-shaped parts 422, 423, 424, 425) may be more generally selected to approximately conform to the expression  $|\beta_2 - \beta_1| = (2n+1) \cdot 90^\circ$ , with n representing an integer, for example to consider also relative arrangements where incoming light is used having a polarization plane which is not necessarily aligned with the x- or y-direction. With the embodiments as described in connection with Fig. 4f it is also possible to approximate polarization distributions with a tangential polarization.

**[0073]** In order to produce a tangential polarization distribution from linearly polarized light with a wave length of 193 nm and a uniform direction of the oscillation plane of the electric field vectors of the individual light rays, one can use for example a polarization-modulating optical element of crystalline quartz with the design according to Figures 3 and 4d. The specific rotation  $\alpha$  of quartz for light with a wavelength of 193 nm is in the range of  $(325.2 \pm 0.5)^\circ/\text{mm}$ , which was measured at a wavelength of 180 nm, or more precise it is  $321.1^\circ/\text{mm}$  at  $21.6^\circ\text{C}$ . The strength and effect of the optical activity is approximately constant within a small range of angles of incidence up to 100 mrad. An embodiment could for example be designed according to the following description: An amount of  $276.75 \mu\text{m}$ , which approximately equals  $90^\circ/\alpha$ , is selected for the minimum thickness  $d_{\min}$ , if crystalline quartz is used. Alternatively, the minimum thickness  $d_{\min}$  can also be an integer multiple of this amount. The element diameter is 110 mm, with the diameter of the optically active part being somewhat smaller, for example 105 mm. The base surface is designed as a planar surface as illustrated in Figure 3. The opposite surface has a thickness profile  $d(r,\theta)$  in accordance with Figure 4d. The thickness profile is defined by the following mathematical relationships:

$$D(r, \theta) = 276.75 + \frac{180^\circ - \theta}{180^\circ} \cdot 553.51 \mu\text{m} \text{ for } 0 \leq \theta \leq 180^\circ$$

5

and

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$$r > \frac{10.5}{2} \text{ mm}$$

15

$$D(r, \theta) = 276.75 + \frac{360^\circ - \theta}{180^\circ} \cdot 553.51 \mu\text{m} \text{ for } 180^\circ \leq \theta \leq 360^\circ \text{ and}$$

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$$r > \frac{10.5}{2} \text{ mm}$$

25

$$D(r, \theta) = 0 \quad \text{for } r \leq \frac{10.5}{2} \text{ mm}$$

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**[0074]** The above mentioned data are based exemplarily for a specific rotation  $\alpha$  of  $(325.2 \pm 0.5)^\circ/\text{mm}$ . If the specific rotation  $\alpha$  changes to  $321.1^\circ/\text{mm}$ , the value at 193 nm and at a temperature of  $21.6^\circ\text{C}$ , the thickness profile will change as follows:

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$$D(r, \theta) = 278.6 + \frac{180^\circ - \theta}{180^\circ} \cdot 557 \mu\text{m} \quad \text{for } 0 \leq \theta \leq 180^\circ \quad \text{and} \quad r > \frac{10.5}{2} \text{ mm}$$

40

$$D(r, \theta) = 278.6 + \frac{360^\circ - \theta}{180^\circ} \cdot 557 \mu\text{m} \quad \text{for } 180^\circ \leq \theta \leq 360^\circ \text{ and} \quad r > \frac{10.5}{2} \text{ mm}$$

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$$D(r, \theta) = 0 \quad \text{for } r \leq \frac{10.5}{2} \text{ mm}$$

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**[0075]** The polarization-modulating optical element according to this embodiment has a central opening 407 with a diameter 10.5, i.e., one-tenth of the maximum aperture. The thickness maxima and minima, which are found at the discontinuities, are  $830.26 \mu\text{m}$  and  $276.75 \mu\text{m}$ , respectively for the first given example.

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**[0076]** The embodiment of the foregoing description can be produced with a robot-polishing process. It is particularly advantageous to produce the polarization-modulating element from two wedge-shaped or helically shaped half-plates which are seamlessly joined together after polishing. If the element is produced by half-plates, it is easy and in some applications of additional advantage to use one clockwise and one counterclockwise optically active material like clockwise crystalline and counterclockwise crystalline quartz (R-quartz and L-quartz).

**[0077]** Figure 5 schematically illustrates how a polarization-modulating optical element 501 with a thickness profile according to Figures 3 and 4d converts the polarization distribution of an entering light bundle 513 with a uniformly

oriented linear polarization distribution 517 into a tangential polarization 519 of an exiting light bundle 515. This can be visualized as follows: A linearly polarized light ray of the entering light bundle 513 which traverses the polarization-modulating optical element at a location of minimum thickness, for example at  $\theta = 180^\circ$ , covers a distance of  $90^\circ/\alpha$  inside the optically active crystal. This causes the oscillation plane of the electrical field vector to be rotated by  $90^\circ$ . On the other hand, a linearly polarized light ray traversing the polarization-modulating optical element 501 at a location with  $\theta = 45^\circ$  covers a distance of  $135^\circ/\alpha$  inside the optically active crystal, thus the oscillation plane of the electrical field vector of this ray is rotated by  $135^\circ$ . Analogous conclusions can be drawn for each light ray of the entering light bundle 513.

**[0078]** Figure 6 schematically illustrates how an optical arrangement with a polarization-modulating optical element 601 with a thickness profile according to Figures 3 and 4d in combination with a further polarization-modulating element 621 converts the polarization distribution of an entering light bundle 613 with a uniformly oriented linear polarization distribution 617 into a radial polarization 623 of an exiting light bundle 615. As explained in the context of Figure 5, the polarization-modulating optical element 601 produces a tangential polarization distribution. A tangential polarization distribution can be converted into a radial polarization distribution by a  $90^\circ$ -rotation of the respective oscillation plane of each individual linearly polarized ray of the light bundle. There are several different possibilities to accomplish this with an optical arrangement according to Figure 6. One possible concept is to arrange a planar-parallel plate of an optically active crystal as a further polarization-modulating element 621 in the light path, where the thickness of the plate is approximately  $90^\circ/\alpha_p$  with  $\alpha_p$  representing the specific rotation of the optically active crystal. As in the polarization-modulating element 601, the optical crystal axis of the planar parallel plate runs likewise parallel to the element axis. As another possible concept, the further polarization-modulating element 621 can be configured as a  $90^\circ$ -rotator that is assembled from two half-wave plates. A  $90^\circ$ -rotator consists of two half-wave plates of birefringent crystal material. Each plate has a slow axis associated with the direction of the higher refractive index and, perpendicular to the slow axis, a fast axis associated with the direction of the lower refractive index. The two half-wave plates are rotated relative to each other so their respective fast and slow axes are set at an angle of  $45^\circ$  from each other.

**[0079]** Of course further possible embodiments for producing a radial polarization distribution are conceivable within the scope of the invention. For example, the further polarization-modulating optical element 621 can be connected to the polarization-modulating optical element 601. To allow a fast change-over from tangential to radial polarization, one could provide an exchange device that allows the further polarization-modulating element 621 to be placed in the light path and to be removed again or to be replaced by another element.

**[0080]** A tangential polarization distribution can also be produced with a polarization-modulating optical element that has a thickness profile in accordance with figure 4e. The thickness profile in this embodiment of the invention has no discontinuities. As visualized in Figure 7a, the uniformly oriented polarization distribution 717 of the entering light bundle 713 is first transformed by the polarization-modulating optical element 701 into a linear polarization distribution 727 of an exiting light bundle 715. The one-half of the entering light bundle 713 that passes through the polarization-modulating optical element 701 in the azimuth range  $0 \leq \theta \leq 180^\circ$  of the thickness profile shown in Figure 4e is converted so that the corresponding one-half of the exiting light bundle has a tangential polarization distribution. The other half, however, has a different, non-tangential polarization distribution 727. A further polarization-modulating optical element is needed in the light path in order to completely convert the polarization distribution 727 of the light bundle 715 exiting from the polarization-modulating optical element 701 into a tangential polarization distribution 719. The further polarization-modulating optical element is in this case configured as a planar-parallel plate 725 with a first half 729 and a second half 731. A plan view of the planar-parallel plate 725 is shown in Figure 7b. The first half 729 is made of an isotropic material that has no effect on the state of polarization of a light ray, while the second half 731 is designed as a half-wave plate. The planar-parallel plate 725 in the optical arrangement of Figure 7a is oriented so that a projection RA' of the reference axis RA of the polarization-modulating optical element 701 onto the planar-parallel plate runs substantially along the separation line between the first half 729 and the second half 731. The slow axis LA of the birefringence of the half-wave plate is perpendicular to this separation line. Alternatively tangential polarization can also be achieved with a polarization-modulating optical element, having a thickness profile as given by Fig. 4e, if the element is composed of two half wedge-shaped or helically shaped elements of crystalline quartz, wherein the optical activity of one element is clockwise and that of the other is counterclockwise. In this case no additional plane-parallel plate 725 is necessary, as it is in the embodiment of Fig. 7a. In this embodiment preferably each wedge-shaped element has a constant screw-slope, but the slopes have different directions as shown in the profile of Fig. 4e. Further, it is not necessary that the slopes of the geometrical thickness d have the same absolute values, it is sufficient if the slopes D of the optical effective thicknesses have the same absolute values. In this case the specific rotations  $\alpha$  are different regarding absolute values for the two wedge-shaped elements which form the polarization-modulating optical element.

**[0081]** Figure 8 schematically illustrates a microlithography projection system 833 which includes the light source unit 835, the illumination system 839, the mask 853 which carries a microstructure, the projection objective 855, and the substrate 859 that is being exposed to the projection. The light source unit 835 includes a DUV- or VUV-laser, for example an ArF laser for 192 nm, an  $F_2$  laser for 157 nm, an  $Ar_2$  laser for 126 nm or a  $Ne_2$  laser for 109 nm, and a beam-shaping optical system which produces a parallel light bundle. The rays of the light bundle have a linear polarization distribution

where the oscillation planes of the electrical field vectors of the individual light rays are oriented in a uniform direction. The principal configuration of the illumination system 839 is described in DE 195 29 563 (US 6,258,433). The parallel light bundle falls on the divergence-increasing optical element 837. As a divergence-increasing optical element, one could use for example a raster plate with an arrangement of diffractive or refractive raster elements. Each raster element generates a light bundle whose angle distribution is determined by the dimension and focal length of the raster element. The raster plate is located in or near the object plane of an objective 840 that follows downstream in the light path. The objective 840 is a zoom objective which generates a parallel light bundle with a variable diameter. A direction-changing mirror 841 directs the parallel light bundle to an optical unit 842 which contains an axicon (i.e., a rotationally symmetric prism arrangement) 843. The zoom objective 840 in cooperation with the axicon 843 generates different illumination profiles in the pupil plane 845, depending on the setting of the zoom and the position of the axicon elements. A polarization-modulating optical element 801, for example of the kind shown in Figure 3, is arranged in the pupil plane 845. The polarization-modulating optical element 801 is followed in the light path by a compensation plate 847 which has a thickness profile designed to compensate the angle deviations which the polarization-modulating optical element causes in the light rays that pass through it. The optical unit 842 is followed by a reticle-masking system (REMA) 849. The REMA Objective 851 projects an image of the reticle-masking system 849 onto the structure-carrying mask (reticle) 853, whereby the illuminated area of the reticle 853 is delimited. The projection objective 855 projects the image of the structure-carrying mask 853 onto the light-sensitive substrate 859. The space between the last optical element 857 of the projection objective and the light-sensitive substrate 859 contains an immersion liquid 861 with a refractive index different from air.

**[0082]** An additional advantage of the present invention is that polarization-modulating optical elements or the optical system according to the present invention can be used for adjusting the polarization distribution and also for temperature compensation of the polarization distribution in a microlithography projection system as described in Fig. 8. Advanced microlithography projection systems require in some applications a predefined polarization distribution at the reticle 853 with an accuracy of about  $5^\circ$  or even better, in some cases even better than  $1^\circ$ .

**[0083]** Since the polarization distribution at the reticle is influenced by the various optical elements by e.g. tension-induced birefringence, or by undefined or uncontrolled changes of the temperature of individual optical elements, the polarization distribution can unpredictably or uncontrollably change over time. To correct such changes the temperature dependency of the specific rotation  $\alpha$  of the polarization-modulating optical element can be used to control the magnitude of the polarization angles. The optical system according to an embodiment of the present invention preferably comprises a polarization control system for controlling the polarization distribution of the light beam which is propagating through the optical system. The polarization distribution of interest is at a predefined location in the optical system. The polarization control system comprises at least one heating or cooling device to modify the temperature and/or the temperature distribution of the polarization-modulating optical element to affect the polarization distribution of the light beam at the predefined location. Here the polarization-modulating optical element may have a varying or constant effective optical thickness.

**[0084]** In the case of a constant effective optical thickness the optical system comprises an optical axis or a preferred direction given by the direction of a light beam propagating through the optical system. The optical system additionally comprises a polarization-modulating optical element described by coordinates of a coordinate system, wherein one preferred coordinate of the coordinate system is parallel to the optical axis or parallel to said preferred direction. The polarization-modulating optical element comprises solid and/or liquid optically active material, wherein the effective optical thickness is constant as a function of at least one coordinate different from the preferred coordinate of the coordinate system. The optical system comprises further a polarization control system for controlling the polarization distribution of the light beam (propagating through the optical system) at a predefined location in the optical system, and the polarization control system comprises at least one heating or cooling device to modify the temperature and/or the temperature distribution of the polarization-modulating optical element to affect the polarization distribution of the light beam at the predefined location.

**[0085]** As an example, if the polarization-modulating optical element (as used e.g. in the optical system according to the present invention) is made of synthetic (crystalline) quartz, comprising a parallel plate or formed as a parallel plate, a thickness of 10 mm of such a plate will result in a change of polarization of  $23.6 \text{ mrad}/^\circ\text{C}$  or  $23.6 \text{ mrad}/\text{K}$ , equivalent to  $1.35^\circ/\text{K}$ , due to the linear temperature coefficient  $\gamma$  of the specific rotation  $\alpha$  with  $\gamma = 2.36 \text{ mrad}/(\text{mm}\cdot\text{K})$ . These data correspond to a wavelength of 193 nm. In such an embodiment, which is schematically shown in Fig. 9, the optical axis OA of the parallel plate 901 is directed parallel or approximately parallel to the propagation of the light (indicated by reference numeral 950) in the optical system. Approximately parallel means that the angle between the optical axis OA of the parallel plate 901 and the direction of the light propagating through the optical system is smaller than  $200 \text{ mrad}$ , preferably smaller than  $100 \text{ mrad}$  or even smaller than  $50 \text{ mrad}$ . Controlling the temperature of the plate 901 will result in a controlled change of polarization. If for example the temperature of the plate will be controlled in a range of about  $20^\circ\text{C}$  to  $40^\circ\text{C}$ , the polarization angles can be controllably changed in a range of about  $\pm 13.5^\circ$  for such a plate 901 made of quartz. This high sensitivity allows a control of the polarization distribution by temperature control. In such a case even a plane plate with a thickness  $d$  of about 0.1 mm up to 20 mm will become a polarization-modulating optical element

901, able to controllably adjust a polarization distribution by controlling the temperature of the plate 901. Preferably for synthetic (crystalline) quartz the thickness of the plate 901 is  $n \cdot 278.5 \mu\text{m}$  ( $n$  is any integer) which results in a rotation of a polarization plane of at least  $90^\circ$  for  $n=1$  and  $180^\circ$  for  $n=2$  and in general  $n \cdot 90^\circ$ , for a wavelength of 193 nm at about  $21.6^\circ\text{C}$ . For a  $90^\circ$  rotation of the polarization plane the synthetic quartz should be at least  $278.5 \mu\text{m}$  thick and for  $180^\circ$  at least  $557.1 \mu\text{m}$ , for  $270^\circ$  the thickness should be  $835.5 \mu\text{m}$  and for a  $360^\circ$  rotation of the polarization the thickness is  $1.114 \text{ mm}$ . The manufacturing tolerances regarding thickness are about  $\pm 2 \mu\text{m}$ . Thus the manufacturing tolerance results in an inaccuracy of the angle of the polarization plane of the light which passes the plate of about  $\pm 0.64^\circ$  at about  $21.6^\circ\text{C}$  and 193 nm. To this inaccuracy an additional inaccuracy caused by temperature fluctuation of the plate (or polarization-modulating optical element) have to be considered, which is given by the linear temperature coefficient  $\gamma$  of the specific rotation  $\alpha$  with is  $\gamma = 2.36 \text{ mrad}/(\text{mm} \cdot \text{K}) = 0.15^\circ/(\text{mm} \cdot \text{K})$ .

**[0086]** The temperature control of the plate 901 can be done by closed-loop or open-loop control, using a temperature sensing device with at least one temperature sensor 902, 903 for determining the temperature of the plate 901 (or providing a temperature sensor value which is representative or equal to the temperature and/or the temperature distribution of the polarization-modulating optical element), at least a heater 904, 905, preferably comprising an infrared heater, for heating the plate by infrared radiation 906, and a control circuit 910 for controlling the at least one heater 904, 905. As an example of a temperature sensing device a infrared sensitive CCD-element with a projection optics may be used, wherein the projection optics images at least a part of the plate 901 onto the CCD-element such that a temperature profile of the viewed part of the plate 901 can be determined by the analysis of the CCD-element signals. The control circuit 910 may comprise a computer system 915 or may be connected to the computer or control system 915 of the microlithography projection system 833 (see Fig. 8). In a preferred embodiment of the temperature controlled plate 901 the thickness is chosen such that a rotation of the polarization of  $n \cdot 90^\circ$ ,  $n$  is any integer number, is achieved at a temperature  $T = (T_{\text{max}} - T_{\text{min}}) / 2 + T_{\text{min}}$ , whereas  $T_{\text{max}}$  and  $T_{\text{min}}$  are the maximum and minimum temperatures of the plate 901 (or in general the polarization-manipulating optical element). Preferably the heater or heating system (and also any cooling device like a Peltier element) is arranged such that it is not in the optical path of the microlithography projection system 833, or that it is not in the optical path of the light beam which is propagating through the optical system according to an embodiment of the present invention. Preferably the optical system with the polarization control system according to the present invention is used in a system with at least one additional optical element arranged between the polarization-modulating optical element and the predefined location in the optical system such that the light beam contacts the at least one additional optical element when propagating from the polarization-modulating optical element to the predefined location. The additional optical element preferably comprises a lens, a prism, a mirror, a refractive or a diffractive optical element or an optical element comprising linear birefringent material. Thus the optical system according to the present invention may form a part of a microlithography projection system 833.

**[0087]** In a further preferred embodiment the temperature of the polarization-manipulating optical element 901 (the plate as shown in Fig. 9) corresponds to a predefined temperature profile. As an example, such a temperature profile is achieved by using a plurality of infrared heaters 904, 905 to produce a radiation distribution across the optical element 901 which heats the optical element 901 in a controlled way with a control circuit as already described. In such an embodiment also a plurality of temperature sensors 902, 903 can be used for the control circuit 910. With this embodiment the polarization state in a field plane or pupil plane of the microlithography projection system 833 can be adjusted locally.

**[0088]** Alternatively or in addition the heater or heating elements 904, 905 may be replaced or supplemented by one or more Peltier-elements 907, 908. The Peltier-element or elements are preferably connected to the control circuit 910 such that a control by open and/or closed loop control is possible. The advantage of the Peltier-elements is that also a controlled cooling of the polarization-manipulating optical element 901 can be achieved. Heating and cooling the optical element 901 at the same time result in complex temperature distributions in the polarization-modulating optical element 901, which result in complex polarization distributions of the light 950 propagating e.g. through the microlithography projection system 833, after passing the element 901. Of course, other heating and cooling means than the ones mentioned above can be used to achieve a required temperature profile or a required temperature of the polarization-modulating optical element 901.

**[0089]** The application of the plane plate 901 as polarization-modulating optical element 801 in the illumination system of a microlithography projection apparatus 833 (see Fig. 8) is preferably in the pupil plane 845 and/or at positions between the light source unit 835 and the mentioned pupil plane 845. Applying the plane plate 901 at these locations has the advantage that the angle of incidence of the light which passes through the plate 901 and also passing through the microlithography projection apparatus is smaller than about  $6^\circ$  (100 mrad). At these small angles the influence of linear birefringence, caused by the plate 901, is very small such that the polarization of the light after passing the plate 901 is almost linear with negligible elliptical parts, if the light was linearly polarized before entering the plate 901.

**[0090]** In a further preferred embodiment of the invention the state of the polarization of the light passed through the polarization-modulating element 901 or the optical system according to the present invention is measured. For this the polarization control system comprises a polarization measuring device providing a polarization value representative for or equal to the polarization or the polarization distribution of the light beam at the predetermined location in the optical

system. Further, the control circuit controls the at least one heating or cooling device dependent on the temperature sensor value and/or the polarization value by open or closed loop control. The measured state of polarization is compared with a required state and in the case that the measured state deviates more than a tolerable value, the temperature and/or the temperature distribution of the polarizing-modulating element like the plane plate 901 is changed such that the difference between the measured and the required state of polarization becomes smaller, and if possible such small that the difference is within a tolerable value. In Fig. 9 the measurement of the state of polarization is measured in-situ or with a separate special measurement, depending on the polarization measuring device 960. The polarization measuring device may be connected with the control circuit 910, such that depending on the measured polarization state values the heating means 904, 905 and/or 907, 908 are controlled heated and/or cooled such that the measured and the required state of polarization becomes smaller. The control can be done in open or closed loop modus.

**[0091]** The plane plate 901 used as polarization-modulating optical element or being a part of such element is especially appropriate to correct orientations of polarization states of the passed light bundles.

**[0092]** In a further embodiment of the present invention the plane plate 901 (comprising or consisting of optically active material), used as a polarization-modulating optical element, is combined with a plate 971 (see Fig. 10), comprising or consisting of linear birefringent material. With this embodiment of the invention the orientation and the phase of the passing light bundle 950 can be subjected such that e.g. a plane polarized light bundle becomes elliptically polarized after passing both plane plates 901 and 971, or vice versa. In this embodiment at least one plate 901 or 971 is controlled regarding its temperature and/or temperature distribution as described in connection with Fig. 9. Further, the sequence of the plates 901 and 971 may be changed such that the passing light bundles are first passing through the plate 971, comprising or consisting of linear birefringent material, and than through the plate 901, comprising or consisting of optical active material, or vice versa. Preferably both plates are consecutively arranged along the optical axis OA of the system. Also, more than one plate comprising or consisting of linear birefringent material, and/or more than one plate comprising or consisting of optical active material may be used to manipulate the state of polarization of the passing light bundles. Further, a plane plate 971, or 901 may be exchanged by a liquid cell or cuvette containing optically active material. Also the plane plates 971, comprising or consisting of linear birefringent material, and plate 901, comprising or consisting of optical active material, can be arranged such that at least one other optical element 981 is placed between these plane plates. This element 981 can be for example a lens, a diffractive or refractive optical element, a mirror or an additional plane plate.

**[0093]** In an additional embodiment of the present invention a polarization-modulating element or in general a polarizing optical element is temperature compensated to reduce any inaccuracy of the polarization distribution generated by the polarization-modulating element due to temperature fluctuations of said element, which for synthetic quartz material is given by the linear temperature coefficient  $\gamma$  of the specific rotation  $\alpha$  for quartz (which is as already mentioned above  $\gamma = 2.36 \text{ mrad}/(\text{mm}\cdot\text{K}) = 0.15^\circ/(\text{mm}\cdot\text{K})$ ). The temperature compensation makes use of the realization that for synthetic quartz there exist one quartz material with a clockwise and one quartz material with a counterclockwise optical activity (R-quartz and L-quartz). Both, the clockwise and the counterclockwise optical activities are almost equal in magnitude regarding the respective specific rotations  $\alpha$ . The difference of the specific rotations is less than 0,3%. Whether the synthetic quartz has clockwise (R-quartz) or counterclockwise (L-quartz) optical activity depends on the seed-crystal which is used in the manufacturing process of the synthetic quartz.

**[0094]** R- and L-quartz can be combined for producing a thermal or temperature compensated polarization-modulating optical element 911 as shown in Fig. 11. Regarding the change of the state of polarization such a temperature compensated polarization-modulating optical element 911 is equivalent to a plane plate of synthetic quartz of thickness  $d$ . For example, two plane plates 921 and 931 are arranged behind each other in the direction 950 of the light which is propagating through the optical system which comprises the temperature compensated polarization-modulating optical element 911. The arrangement of the plates is such that one plate 931 is made of R-quartz with thickness  $d_R$ , and the other 921 is made of L-quartz with thickness  $d_L$ , and  $|d_R - d_L| = d$ . If the smaller thickness of  $d_R$  and  $d_L$  ( $\min(d_R, d_L)$ ) is larger than  $d$  or  $\min(d_R, d_L) > d$ , which in most cases is a requirement due to mechanical stability of the optical element, then the temperature dependence of the polarization state becomes partly compensated, meaning that the temperature dependence of the system of R-quartz and L-quartz plates is smaller than  $\gamma = 2.36 \text{ mrad}/(\text{mm}\cdot\text{K})\cdot d = 0.15^\circ/(\text{mm}\cdot\text{K})\cdot d$ , wherein  $d$  is the absolute value of the difference of the thicknesses of the two plates  $d = |d_R - d_L|$ . The following example demonstrates this effect. A R-quartz plate 931 with a thickness of e.g.  $d_R = 557.1 \mu\text{m}$  (resulting in a  $180^\circ$  clockwise change of the exiting polarization plane compared to the incident polarization plane) is combined with a L-quartz plate 921 with a thickness of  $d_L = 557.1 \mu\text{m} + 287.5 \mu\text{m}$  (resulting in a  $270^\circ$  counterclockwise change of the exiting polarization plane compared to the incident polarization). This result in a  $90^\circ$  counterclockwise change of the polarization plane after the light pass both plane plates 921, 931, corresponding to a  $270^\circ$  clockwise change of the polarization plane if just a R-quartz plate would be used. In this case the temperature compensation is not fully achieved, but it is reduced to value of about  $0.04^\circ/\text{K}$  if both plates are used, compared to  $0,13^\circ/\text{K}$  if just a R-quartz plate of  $d_R = 557.1 \mu\text{m} + 287.5 \mu\text{m}$  would be used. This is a significant reduction of temperature dependency, since even if the temperature will change by  $10^\circ\text{C}$  the change of the polarization plane is still smaller than  $1^\circ$ .

**[0095]** In general any structured polarization-modulating optical element made of R- or L-quartz, like e.g. the elements as described in connection with Figures 3 and 4a can be combined with a plane plate of the respective other quartz type (L- or R-quartz) such that the combined system 911 will have a reduced temperature dependence regarding the change of the polarization. Instead of the plane plate also a structured optical element made of the respective other quartz type may be used such that in Fig. 11 the shown plates 921 and 931 can be structured polarization-modulating optical elements as mentioned in this specification, having specific rotations of opposite signs, changing the state of polarization clockwise and counterclockwise.

**[0096]** To generalize the above example of a temperature compensated polarization-modulating optical element 911, the present invention also relates to an optical system comprising an optical axis OA or a preferred direction 950 given by the direction of a light beam propagating through the optical system. The optical system comprising a temperature compensated polarization-modulating optical element 911 described by coordinates of a coordinate system, wherein one preferred coordinate of the coordinate system is parallel to the optical axis OA or parallel to said preferred direction 950. The temperature compensated polarization-modulating optical element 911 comprises a first 921 and a second 931 polarization-modulating optical element. The first and/or the second polarization-modulating optical element comprising solid and/or liquid optically active material and a profile of effective optical thickness, wherein the effective optical thickness varies at least as a function of one coordinate different from the preferred coordinate of the coordinate system. In addition or alternative the first 921 and/or the second 931 polarization-modulating optical element comprises solid and/or liquid optically active material, wherein the effective optical thickness is constant as a function of at least one coordinate different from the preferred coordinate of the coordinate system. As an additional feature, the first and the second polarization-modulating optical elements 921, 931 comprise optically active materials with specific rotations of opposite signs, or the first polarization-modulating optical element comprises optically active material with a specific rotation of opposite sign compared to the optically active material of the second polarization-modulating optical element. In the case of plane plates, preferably the absolute value of the difference of the first and the second thickness of the first and second plate is smaller than the thickness of the smaller plate.

**[0097]** In an additional embodiment of the present invention a polarization-modulating element comprises an optically active and/or optically inactive material component subjected to a magnetic field such that there is a field component of the magnetic field along the direction of the propagation of the light beam through the polarization-modulating element. The optical active material component may be construed as described above. However, also optical inactive materials can be used, having the same or similar structures as described in connection with the optical active materials. The application of a magnetic field will also change the polarization state of the light passing through the optical active and/or optical inactive material due to the Faraday-effect, and the polarization state can be controlled by the magnetic field.

**[0098]** Various embodiments for a polarization-modulating optical element or for the optical systems according to the present invention are described in this application. Further, also additional embodiments of polarization-modulating optical elements or optical systems according to the present invention may be obtained by exchanging and/or combining individual features and/or characteristics of the individual embodiments described in the present application.

## Claims

1. A projection system, comprising:

- a radiation source, an illumination system operable to illuminate a structured mask, and a projection objective for projecting an image of the mask structure onto a light-sensitive substrate, said illumination system having an optical system axis defined by the propagation of a light beam through the illumination system; and
- a polarization-modulating optical element which has a thickness profile or comprises a thickness profile and consists of or comprises an optically active crystal with an optical axis parallel to said optical system axis, wherein the thickness profile varies as measured in the direction of the optical axis of said optically active crystal;
- wherein said polarization-modulating optical element is arranged in a pupil plane of the illumination system.

2. The projection system according to claim 1, wherein the polarization-modulating optical element transforms an entering light bundle with a first linear polarization distribution into an exiting light bundle with a second linear polarization distribution, wherein the first linear polarization distribution is different from the second linear polarization distribution.

3. The projection system according to claim 2, wherein the polarization distribution of the exiting light bundle is an approximately tangential polarization distribution or an approximately radial polarization distribution.

4. The projection system according to anyone of the claims 1 to 3, wherein respective planes of oscillation of a first

linearly polarized light ray and a second linearly polarized light ray are rotated, respectively, by a first angle of rotation and a second angle of rotation in such a way that the first angle of rotation is different from the second angle of rotation.

5 5. The projection system according to anyone of the claims 1 to 4, wherein the optically active crystal is quartz, TeO<sub>2</sub> or AgGaS<sub>2</sub>.

10 6. The projection system according to one of the preceding claims, wherein the polarization-modulating optical element has an element axis oriented substantially in the direction of the optical axis of the optically active crystal, and wherein the thickness profile in relation to the element axis has a variation that depends only on an azimuth angle  $\theta$ , the azimuth angle  $\theta$  being measured from a reference axis that runs perpendicular to the element axis and intersects the element axis.

15 7. The projection system according to claim 6, wherein the thickness profile has a constant value along a radius that is oriented perpendicularly to the element axis and at an angle  $\theta$  relative to the reference axis.

8. The projection system according to claim 6 or 7, wherein an azimuthal section  $d(r=\text{const.},\theta)$  of the thickness profile  $d(r,\theta)$  in a range of azimuth angles  $10^\circ < \theta < 350^\circ$  and at a constant distance  $r$  from the element axis is a linear function of the azimuth angle  $\theta$ , wherein this azimuthal section has a slope  $m$  conforming approximately to the

20 expression  $|m| = \frac{180^\circ}{\alpha \pi r}$ , with  $\alpha$  representing the specific rotation of the optically active crystal.

25 9. The projection system according to claim 8, wherein the azimuthal section  $d(r=\text{const.},\theta)$  has a substantial jump-like increase of  $360^\circ/\alpha$  at the azimuth angle  $\theta=0^\circ$ .

30 10. The projection system according to claim 6 or 7, wherein an azimuthal section  $d(r=\text{const.},\theta)$  of the thickness profile  $d(r,\theta)$  in a range of azimuth angles  $10^\circ < \theta < 170^\circ$  and  $190^\circ < \theta < 350^\circ$  at a constant distance  $r$  from the element axis is a linear function of the azimuth angle  $\theta$ , wherein this azimuthal section has a slope  $m$  conforming approximately

to the expression  $|m| = \frac{180^\circ}{\alpha \pi r}$ , with  $\alpha$  representing the specific rotation of the optically active crystal.

35 11. The projection system according to claim 10, wherein the azimuthal section  $d(r=\text{const.},\theta)$  has a substantially jump-like increase of  $180^\circ/\alpha$  at the azimuth angles  $\theta=0^\circ$  and  $\theta=180^\circ$ .

40 12. The projection system according to claim 6 or 7, wherein an azimuthal section  $d(r=\text{const.},\theta)$  of the thickness profile  $d(r,\theta)$  at a constant distance  $r$  from the element axis and in a first azimuth angle range of  $10^\circ < \theta < 170^\circ$  is a linear function of the azimuth angle  $\theta$  with a first slope  $m$ , while in a second azimuth angle range of  $190^\circ < \theta < 350^\circ$ , the azimuthal section is a linear function of the azimuth angle  $\theta$  with a second slope  $n$ , wherein the slopes  $m$  and  $n$  have the same absolute magnitude but opposite signs, and wherein the magnitude of the slopes  $m$  and  $n$  conforms to

the expression  $|m| = |n| = \frac{180^\circ}{\alpha \pi r}$  with  $\alpha$  representing the specific rotation of the optically active crystal.

45 13. The projection system according to one of the claims 1-7, wherein the polarization-modulating optical element consists of or comprises at least two planar-parallel portions of different thickness or different optical effective thickness.

50 14. The projection system according to claim 13, wherein the portions are configured as sectors of a circle, or as hexagonal, square, rectangular, or trapeze-shaped raster elements and/or comprise at least a cuvette comprising an optically active or optically inactive liquid.

55 15. The projection system according to claim 13 or 14, wherein a pair of first plan-parallel portions are arranged on opposite sides of a central element axis of the polarization-modulating optical element, and wherein a pair of second plan-parallel portions are arranged on opposite sides of the element axis and circumferentially displaced around the element axis with respect to the first plan-parallel portions, wherein each of the first portions has a thickness or optical effective thickness being different from a thickness or optical effective thickness of each of the second portions.

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16. The projection system according to claim 15, wherein a plane of oscillation of linearly polarized light passing there through is rotated by a first angle of rotation  $\beta_1$  within at least one of the first plan-parallel portions and by a second angle of rotation  $\beta_2$  within at least one of the second plan-parallel portions, such that  $\beta_1$  and  $\beta_2$  are approximately conforming to the expression  $|\beta_2 - \beta_1| = (2n+1) \cdot 90^\circ$ , with n representing an integer.
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17. The projection system according to claim 16, wherein  $\beta_1$  and  $\beta_2$  are approximately conforming to the expressions  $\beta_1 = 90^\circ + p \cdot 180^\circ$ , with p representing an integer, and  $\beta_2 = q \cdot 180^\circ$  with q representing an integer other than zero.
- 15
18. The projection system according to anyone of the claims 15-17, wherein the pair of second plan-parallel portions is circumferentially displaced around the element axis with respect to the pair of first plan-parallel portions by approximately  $90^\circ$ .
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19. The projection system according to anyone of the claims 15-18, wherein the pair of first plan-parallel portions and the pair of second plan-parallel portions are arranged on opposite sides of a central opening or a central obscuration of the polarization-modulating optical element.
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20. The projection system according to anyone of the claims 15-19, wherein adjacent portions of the first and second pairs are spaced apart from each other by regions being opaque or not optically active to linearly polarized light entering the polarization-modulating optical element.
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21. The projection system according to anyone of the claims 15-20, wherein the portions of the first and second pair are held together by a mounting.
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22. The projection system according to claim 21, wherein the mounting is opaque or not optically active to linearly polarized light entering the polarization-modulating optical element.
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23. The projection system according to claim 21 or 22, wherein the mounting has a substantially spoke-wheel shape.
- 45
24. The projection system according to anyone of the claims 13-23, comprising a first group of substantially planar-parallel portions wherein a plane of oscillation of traversing linearly polarized light is rotated by a first angle of rotation  $\beta_1$ , and a second group of substantially planar-parallel portions wherein a plane of oscillation of traversing linearly polarized light is rotated by a second angle of rotation, such that  $\beta_1$  and  $\beta_2$  are approximately conforming to the expression  $|\beta_2 - \beta_1| = (2n+1) \cdot 90^\circ$ , with n representing an integer.
- 50
25. The projection system according to claim 24, wherein  $\beta_1$  and  $\beta_2$  are approximately conforming to the expressions  $\beta_1 = 90^\circ + p \cdot 180^\circ$ , with p representing an integer, and  $\beta_2 = q \cdot 180^\circ$ , with q representing an integer other than zero.
- 55
26. The projection system according to anyone of the claims 1-7, wherein the thickness profile or profile of effective optical thickness has a continuous shape.
27. The projection system according to anyone of the preceding claims, further having an element diameter D and a minimal thickness  $d_{\min}$ , wherein the minimal thickness  $d_{\min}$  is at least equal to 0.002 times the element diameter D.
28. The projection system according to anyone of the preceding claims, wherein the thickness profile has a minimal thickness  $d_{\min} = N \cdot \frac{90^\circ}{\alpha}$ , with  $\alpha$  representing the specific rotation of the optically active crystal and N representing a positive integer.
29. The projection system according to anyone of the preceding claims, wherein the polarization-modulating optical element has a central opening or a central obscuration.
30. The projection system according to anyone of the preceding claims, wherein the polarization-modulating optical element transforms an entering light bundle with a first polarization distribution into an exiting light bundle with a second polarization distribution, wherein the entering light bundle consists of a multitude of light rays with an angle distribution relative to the optical axis of the optically active crystal, and wherein the angle distribution has a maximum angle of incidence not exceeding 100 mrad.

31. The projection system according to anyone of the preceding claims, wherein an optical arrangement with said polarization-modulating optical element is arranged in the illumination system, wherein the optical arrangement is configured so that at least one further polarization-modulating optical element can be put into the light path.

5 32. The projection system of claim 31, wherein the further polarization-modulating optical element comprises a polarization-modulating optical element which has a thickness profile or comprises a thickness profile and consists of or comprises an optically active crystal with an optical axis, wherein the thickness profile, as measured in the direction of the optical axis of said optically active crystal, is variable.

10 33. The projection system of claim 31, wherein the further polarization-modulating optical element comprises a planar-parallel plate of an optically active crystal and/or a cuvette with optically active or optically inactive liquid.

15 34. The projection system of claim 31, wherein the further polarization-modulating optical element comprises a rotator made of two half-wavelength plates that are rotated by  $45^\circ$  relative to each other.

20 35. The projection system of claim 31, wherein the polarization-modulating optical element has an element axis in reference to which the thickness profile has a variation that depends only on an azimuth angle  $\theta$ , wherein the azimuth angle  $\theta$  is measured from a reference axis that is oriented perpendicular to the element axis and intersects the element axis, wherein the thickness profile in a first azimuth angle range of  $10^\circ < \theta < 170^\circ$  is a linear function of the azimuth angle  $\theta$  with a first slope  $m$ , while in a second azimuth angle range of  $190^\circ < \theta < 350^\circ$  the azimuthal section is a linear function of the azimuth angle  $\theta$  with a second slope  $n$ , wherein the slopes  $m$  and  $n$  have the same absolute magnitude but opposite signs, and wherein the further polarization-modulating optical element comprises a planar-parallel plate which is configured as a half-wavelength plate for a half-space that covers an azimuth-angle range of  $180^\circ$ .

25 36. The projection system of claim 31, wherein the further polarization-modulating optical element causes a  $90^\circ$ -rotation of the oscillation plane of a linearly polarized light ray passing through said optical arrangement.

30 37. The projection system according to anyone of the claims 31 to 36, wherein a compensation plate is arranged in the light path of the optical system, said compensation plate having a thickness profile configured to substantially compensate the angle deviations of transmitted radiation which are caused by the polarization-modulating optical element.

35 38. The projection system according to anyone of the preceding claims, wherein an immersion medium with a refractive index different from air is present between the substrate and an optical element nearest to the substrate.

39. Method of manufacturing micro-structured semiconductor components, comprising a step of using a projection system in accordance with one of the preceding claims.

40 **Patentansprüche**

1. Projektionsbelichtungsanlage, umfassend:

- 45
- eine Strahlungsquelle, eine Beleuchtungseinrichtung, welche zur Beleuchtung einer strukturierten Maske betreibbar ist, und ein Projektionsobjektiv zum Projizieren eines Bildes der Maskenstruktur auf ein lichtempfindliches Substrat, wobei die Beleuchtungseinrichtung eine optische Systemachse aufweist, die durch die Ausbreitung eines Lichtstrahls durch die Beleuchtungseinrichtung definiert ist; und
  - ein polarisationsbeeinflussendes optisches Element, welches ein Dickenprofil aufweist oder ein Dickenprofil umfasst und einen optisch aktiven Kristall mit einer zur optischen Systemachse parallelen optischen Achse enthält oder umfasst, wobei das Dickenprofil gemessen in Richtung der optischen Achse dieses optisch aktiven Kristalls variiert;
  - wobei das polarisationsbeeinflussende optische Element in einer Pupillenebene der Beleuchtungseinrichtung angeordnet ist.
- 50

55 2. Projektionsbelichtungsanlage gemäß Anspruch 1, wobei das polarisationsbeeinflussende optische Element ein eintretendes Lichtbündel mit einer ersten linearen Polarisationsverteilung in ein austretendes Lichtbündel mit einer zweiten linearen Polarisationsverteilung umformt, wobei die erste lineare Polarisationsverteilung von der zweiten

linearen Polarisationsverteilung verschieden ist.

- 5
3. Projektionsbelichtungsanlage gemäß Anspruch 2, wobei die Polarisationsverteilung des austretenden Lichtbündels eine näherungsweise tangentielle Polarisationsverteilung oder eine näherungsweise radiale Polarisationsverteilung ist.
- 10
4. Projektionsbelichtungsanlage gemäß einem der Ansprüche 1 bis 3, wobei jeweilige Schwingungsebenen eines ersten linear polarisierten Lichtstrahls und eines zweiten linear polarisierten Lichtstrahls um einen ersten Drehwinkel bzw. einen zweiten Drehwinkel derart gedreht werden, dass der erste Drehwinkel von dem zweiten Drehwinkel verschieden ist.
- 15
5. Projektionsbelichtungsanlage gemäß einem der Ansprüche 1 bis 4, wobei der optisch aktive Kristall Quarz,  $\text{TeO}_2$  oder  $\text{AgGaS}_2$  ist.
- 20
6. Projektionsbelichtungsanlage nach einem der vorhergehenden Ansprüche, wobei das polarisationsbeeinflussende optische Element eine Elementachse aufweist, welche im Wesentlichen in der Richtung der optischen Achse des optisch aktiven Kristalls orientiert ist, und wobei das Dickenprofil in Bezug auf die Elementachse eine nur von einem Azimutwinkel  $\theta$  abhängige Variation aufweist, wobei der Azimutwinkel  $\theta$  auf eine Referenzachse gemessen ist, welche senkrecht zur Elementachse steht und die Elementachse schneidet.
- 25
7. Projektionsbelichtungsanlage gemäß Anspruch 6, wobei das Dickenprofil entlang eines Radius, welcher senkrecht zur Elementachse und in einem Winkel  $\theta$  relativ zur Referenzachse orientiert ist, einen konstanten Wert aufweist.
- 30
8. Projektionsbelichtungsanlage gemäß Anspruch 6 oder 7, wobei ein azimutaler Schnitt  $d(r=\text{const}, \theta)$  des Dickenprofils  $d(r, \theta)$  in einem Bereich von Azimutwinkeln  $10^\circ < \theta < 350^\circ$  und für einen konstanten Abstand  $r$  von der Elementachse eine lineare Funktion des Azimutwinkels  $\theta$  ist, wobei dieser azimutale Schnitt eine Steigung  $m$  aufweist, welche näherungsweise dem Ausdruck  $|m| = \frac{180^\circ}{\alpha \pi r}$  entspricht, wobei  $\alpha$  das spezifische Drehvermögen des optisch aktiven Kristalls darstellt.
- 35
9. Projektionsbelichtungsanlage gemäß Anspruch 8, wobei der azimutale Schnitt  $d(r=\text{const}, \theta)$  bei dem Azimutwinkel  $\theta=0^\circ$  einen im Wesentlichen sprunghaften Anstieg um  $360^\circ/\alpha$  aufweist.
- 40
10. Projektionsbelichtungsanlage nach Anspruch 6 oder 7, wobei ein azimutaler Schnitt  $d(r=\text{const}, \theta)$  des Dickenprofils  $d(r, \theta)$  in einem Bereich von Azimutwinkeln  $10^\circ < \theta < 170^\circ$  und  $190^\circ < \theta < 350^\circ$  und für einen konstanten Abstand  $r$  von der Elementachse eine lineare Funktion des Azimutwinkels  $\theta$  ist, wobei dieser azimutale Schnitt eine Steigung  $m$  aufweist, welche näherungsweise dem Ausdruck  $|m| = \frac{180^\circ}{\alpha \pi r}$  entspricht, wobei  $\alpha$  das spezifische Drehvermögen des optisch aktiven Kristalls darstellt.
- 45
11. Projektionsbelichtungsanlage gemäß Anspruch 10, wobei der azimutale Schnitt  $d(r=\text{const}, \theta)$  bei den Azimutwinkeln  $\theta = 0^\circ$  und  $\theta = 180^\circ$  jeweils einen im Wesentlichen sprunghaften Anstieg um  $180^\circ/\alpha$  aufweist.
- 50
12. Projektionsbelichtungsanlage gemäß Anspruch 6 oder 7, wobei ein azimutaler Schnitt  $d(r=\text{const}, \theta)$  des Dickenprofils  $d(r, \theta)$  in einem konstanten Abstand  $r$  von der Elementachse und in einem ersten Azimutwinkelbereich  $10^\circ < \theta < 170^\circ$  eine lineare Funktion des Azimutwinkels  $\theta$  mit einer ersten Steigung  $m$  ist, während in einem zweiten Azimutwinkelbereich  $190^\circ < \theta < 350^\circ$  der azimutale Schnitt eine lineare Funktion des Azimutwinkels  $\theta$  mit einer zweiten Steigung  $n$  ist, wobei die Steigungen  $m$  und  $n$  den gleichen Absolutbetrag und entgegengesetzte Vorzeichen aufweisen, wobei für den Betrag der Steigungen  $m$  und  $n$  der Ausdruck gilt:  $|m| = |n| = \frac{180^\circ}{\alpha \pi r}$ , wobei  $\alpha$  das spezifische Drehvermögen des optisch aktiven Kristalls darstellt.
- 55
13. Projektionsbelichtungsanlage gemäß einem der Ansprüche 1-7, wobei das polarisationsbeeinflussende optische

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Element wenigstens zwei planparallele Abschnitte unterschiedlicher Dicke oder unterschiedlicher optisch effektiver Dicke enthält oder umfasst.

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14. Projektionsbelichtungsanlage gemäß Anspruch 13, wobei die Abschnitte als Kreissektoren oder als hexagonale, quadratische, rechteckige oder trapezförmige Rasterelemente konfiguriert sind und/oder wenigstens eine Küvette umfassen, die eine optisch aktive oder optisch inaktive Flüssigkeit umfasst.
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15. Projektionsbelichtungsanlage gemäß Anspruch 13 oder 14, wobei ein Paar von ersten planparallelen Abschnitten auf gegenüberliegenden Seiten einer zentralen Elementachse des polarisationsbeeinflussenden optischen Elements angeordnet ist, und wobei ein Paar von zweiten planparallelen Abschnitten auf gegenüberliegenden Seiten der Elementachse und bezogen auf die ersten planparallelen Abschnitte in Umfangsrichtung um die Elementachse versetzt angeordnet ist, wobei jeder der ersten Abschnitte eine Dicke oder optisch effektive Dicke aufweist, welche sich von einer Dicke oder einer optisch effektiven Dicke jedes der zweiten Abschnitte unterscheidet.
- 15
16. Projektionsbelichtungsanlage gemäß Anspruch 15, wobei eine Schwingungsebene von hindurchtretendem, linear polarisiertem Licht innerhalb wenigstens eines der ersten planparallelen Abschnitte um einen ersten Drehwinkel  $\beta_1$  und innerhalb wenigstens eines der zweiten planparallelen Abschnitte um einen zweiten Drehwinkel  $\beta_2$  derart gedreht wird, dass  $\beta_1$  und  $\beta_2$  näherungsweise den Ausdruck  $|\beta_2 - \beta_1| = (2n+1) \cdot 90^\circ$  erfüllen, wobei n eine ganze Zahl darstellt.
- 20
17. Projektionsbelichtungsanlage gemäß Anspruch 16, wobei  $\beta_1$  und  $\beta_2$  näherungsweise die Ausdrücke  $\beta_1 = 90^\circ + p \cdot 180^\circ$ , wobei p eine ganze Zahl darstellt, und  $\beta_2 = q \cdot 180^\circ$ , wobei q eine ganze Zahl außer Null darstellt, erfüllen.
- 25
18. Projektionsbelichtungsanlage gemäß einem der Ansprüche 15-17, wobei das Paar zweiter planparalleler Abschnitte bezogen auf das Paar erster planparalleler Abschnitte in Umfangsrichtung um die Elementachse um näherungsweise  $90^\circ$  versetzt ist.
- 30
19. Projektionsbelichtungsanlage gemäß einem der Ansprüche 15-18, wobei das Paar erster planparalleler Abschnitte und das Paar zweiter planparalleler Abschnitte auf gegenüberliegenden Seiten einer zentralen Öffnung oder einer zentralen Obskuration des polarisationsbeeinflussenden optischen Elements angeordnet sind.
- 35
20. Projektionsbelichtungsanlage gemäß einem der Ansprüche 15-19, wobei benachbarte Abschnitte des ersten und zweiten Paares voneinander durch für in das polarisationsbeeinflussende optische Element eintretendes linear polarisiertes Licht undurchlässige oder nicht optisch aktive Bereiche beabstandet sind.
- 40
21. Projektionsbelichtungsanlage gemäß einem der Ansprüche 15-20, wobei die Abschnitte des ersten und zweiten Paares über eine Fassung zusammengehalten werden.
- 45
22. Projektionsbelichtungsanlage gemäß Anspruch 21, wobei die Fassung für in das polarisationsbeeinflussende optische Element eintretendes linear polarisiertes Licht undurchlässig oder nicht optisch aktiv ist.
- 50
23. Projektionsbelichtungsanlage gemäß Anspruch 21 oder 22, wobei die Fassung im Wesentlichen eine Speichenradform aufweist.
- 55
24. Projektionsbelichtungsanlage gemäß einem der Ansprüche 13-23, umfassend eine erste Gruppe von im Wesentlichen planparallelen Abschnitten, in denen eine Schwingungsebene von hindurchtretendem linear polarisiertem Licht um einen ersten Drehwinkel  $\beta_1$  gedreht wird, und eine zweite Gruppe von im Wesentlichen planparallelen Abschnitten, in denen eine Schwingungsebene von hindurchtretendem linear polarisiertem Licht um einen zweiten Drehwinkel gedreht wird, so dass  $\beta_1$  und  $\beta_2$  im Wesentlichen den Ausdruck  $|\beta_2 - \beta_1| = (2n+1) \cdot 90^\circ$  erfüllen, wobei n eine ganze Zahl darstellt.
25. Projektionsbelichtungsanlage gemäß Anspruch 24, wobei  $\beta_1$  und  $\beta_2$  näherungsweise die Ausdrücke  $\beta_1 = 90^\circ + p \cdot 180^\circ$ , wobei p eine ganze Zahl darstellt, und  $\beta_2 = q \cdot 180^\circ$ , wobei q eine ganze Zahl außer Null darstellt, erfüllen.
26. Projektionsbelichtungsanlage gemäß einem der Ansprüche 1-7, wobei das Dickenprofil oder das Profil der effektiven optischen Dicke einen kontinuierlichen Verlauf besitzt.
27. Projektionsbelichtungsanlage gemäß einem der vorhergehenden Ansprüche, ferner mit einem Elementdurchmesser D und einer minimalen Dicke  $d_{\min}$ , wobei die minimale Dicke  $d_{\min}$  zumindest das 0.002-fache des Elementdurch-

messers D beträgt.

28. Projektionsbelichtungsanlage gemäß einem der vorhergehenden Ansprüche, wobei das Dickenprofil eine minimale

5 Dicke  $d_{\min} = N \cdot \frac{90^\circ}{\alpha}$  aufweist, wobei  $\alpha$  das spezifische Drehvermögen des optisch aktiven Kristalls darstellt und N eine ganze Zahl darstellt.

- 10 29. Projektionsbelichtungsanlage gemäß einem der vorhergehenden Ansprüche, wobei das polarisationsbeeinflussende optische Element eine zentrale Öffnung oder eine zentrale Obskuration besitzt.

- 15 30. Projektionsbelichtungsanlage gemäß einem der vorhergehenden Ansprüche, wobei das polarisationsbeeinflussende optische Element ein eintretendes Lichtbündel mit einer ersten Polarisationsverteilung in ein austretendes Lichtbündel mit einer zweiten Polarisationsverteilung umformt, wobei das eintretende Lichtbündel aus einer Vielzahl von Lichtstrahlen mit einer Winkelverteilung relativ zur optischen Achse des optisch aktiven Kristalls besteht, und wobei die Winkelverteilung einen maximalen Einfallswinkel aufweist, der 100 mrad nicht übersteigt.

- 20 31. Projektionsbelichtungsanlage gemäß einem der vorhergehenden Ansprüche, wobei eine optische Anordnung mit dem polarisationsbeeinflussenden optischen Element in der Beleuchtungseinrichtung angeordnet ist, wobei die optische Anordnung so konfiguriert ist, dass wenigstens ein weiteres polarisationsbeeinflussendes optisches Element in den Lichtweg eingesetzt werden kann.

- 25 32. Projektionsbelichtungsanlage gemäß Anspruch 31, wobei das weitere polarisationsbeeinflussende optische Element ein polarisationsbeeinflussendes optisches Element umfasst, welches ein Dickenprofil besitzt oder ein Dickenprofil umfasst und einen optisch aktiven Kristall mit einer optischen Achse enthält oder umfasst, wobei das Dickenprofil gemessen in Richtung der optischen Achse des optisch aktiven Kristalls variabel ist.

- 30 33. Projektionsbelichtungsanlage gemäß Anspruch 31, wobei das weitere polarisationsbeeinflussende optische Element eine planparallele Platte aus einem optisch aktiven Kristall und/oder eine Küvette mit einer optisch aktiven oder optisch inaktiven Flüssigkeit umfasst.

- 35 34. Projektionsbelichtungsanlage gemäß Anspruch 31, wobei das weitere polarisationsbeeinflussende optische Element einen Rotator umfasst, welcher aus zwei Halbwellenplatten hergestellt ist, die relativ zueinander um 45° verdreht sind.

- 40 35. Projektionsbelichtungsanlage gemäß Anspruch 31, wobei das polarisationsbeeinflussende optische Element eine Elementachse aufweist, bezogen auf welche das Dickenprofil eine nur von einem Azimutwinkel  $\theta$  abhängige Variation aufweist, wobei der Azimutwinkel  $\theta$  auf eine Referenzachse bezogen ist, welche senkrecht zur Elementachse steht und die Elementachse schneidet, wobei das Dickenprofil in einem ersten Azimutwinkelbereich von  $10^\circ < \theta < 170^\circ$  eine lineare Funktion des Azimutwinkels  $\theta$  mit einer ersten Steigung m ist, während in einem zweiten Azimutwinkelbereich von  $190^\circ < \theta < 350^\circ$  der azimutale Schnitt eine lineare Funktion des Azimutwinkels  $\theta$  mit einer zweiten Steigung n ist, wobei die Steigungen m und n den gleichen Absolutbetrag aber entgegengesetzte Vorzeichen aufweisen, und wobei das weitere polarisationsbeeinflussende optische Element eine planparallele Platte umfasst, welche als Halbwellenplatte für einen Halbraum konfiguriert ist, welcher einen Azimutwinkelbereich von  $180^\circ$  abdeckt.

- 45 36. Projektionsbelichtungsanlage nach Anspruch 31, wobei das weitere polarisationsbeeinflussende optische Element eine 90°-Drehung der Schwingungsebene eines durch die optische Anordnung hindurchtretenden linear polarisierten Lichtstrahls bewirkt.

- 50 37. Projektionsbelichtungsanlage gemäß einem der Ansprüche 31 bis 36, wobei eine Kompensationsplatte im Lichtweg des optischen Elements angeordnet ist, und wobei die Kompensationsplatte ein Dickenprofil aufweist, welches dazu konfiguriert ist, durch das polarisationsbeeinflussende optische Element verursachte Winkelabweichungen von transmittierter Strahlung im Wesentlichen zu kompensieren.

- 55 38. Projektionsbelichtungsanlage gemäß irgendeinem der vorhergehenden Ansprüche, wobei sich ein Immersionsmedium mit einem von Luft verschiedenen Brechungsindex zwischen dem Substrat und einem dem Substrat nächstliegenden optischen Element befindet.

39. Verfahren zum Herstellen von mikrostrukturierten Halbleiterbauelementen, umfassend einen Schritt der Verwendung einer Projektionsbelichtungsanlage gemäß einem der vorhergehenden Ansprüche.

## 5 Revendications

1. Système de projection, comprenant :

10 • une source de rayonnement, un système d'éclairage pouvant être activé pour éclairer un masque structuré, et un objectif de projection destiné à projeter une image de la structure du masque sur un substrat photosensible, ledit système d'éclairage ayant un axe de système optique défini par la propagation d'un faisceau de lumière par l'intermédiaire du système d'éclairage ; et

15 • un élément optique de modulation de la polymérisation qui a un profil d'épaisseur ou comprend un profil d'épaisseur et est constitué de ou comprend un cristal optiquement actif ayant un axe optique parallèle audit axe du système optique, dans lequel le profil d'épaisseur varie lorsqu'il est mesuré dans la direction de l'axe optique dudit cristal optiquement actif ;

• dans lequel ledit élément optique de modulation de la polymérisation est agencé dans un plan de pupille du système d'éclairage.

- 20 2. Système de projection selon la revendication 1, dans lequel l'élément optique de modulation de la polarisation transforme un faisceau de lumière entrant ayant une première distribution de polarisation linéaire en un faisceau de lumière sortant ayant une deuxième distribution de polarisation linéaire, où la première distribution de polarisation linéaire est différente de la deuxième distribution de polarisation linéaire.

- 25 3. Système de projection selon la revendication 2, dans lequel la distribution de polarisation du faisceau de lumière sortant est une distribution de polarisation approximativement tangentielle ou une distribution de polarisation approximativement radiale.

- 30 4. Système de projection selon l'une quelconque des revendications 1 à 3, dans lequel les plans respectifs d'oscillation d'un premier rayon lumineux polarisé linéairement et d'un deuxième rayon lumineux polarisé linéairement sont entraînés en rotation, respectivement, d'un premier angle de rotation et d'un deuxième angle de rotation de telle sorte que le premier angle de rotation est différent du deuxième angle de rotation.

- 35 5. Système de projection selon l'une quelconque des revendications 1 à 4, dans lequel le cristal optiquement actif est constitué de quartz, de  $\text{TeO}_2$  ou de  $\text{AgGaS}_2$ .

- 40 6. Système de projection selon l'une quelconque des revendications précédentes, dans lequel l'élément optique de modulation de la polarisation comporte un axe d'élément orienté sensiblement dans la direction de l'axe optique du cristal optiquement actif, et dans lequel le profil d'épaisseur par rapport à l'axe d'élément présente une variation qui dépend uniquement d'un angle d'azimut  $\theta$ , l'angle d'azimut  $\theta$  étant mesuré par rapport à un axe de référence qui s'étend perpendiculairement à l'axe d'élément et coupe l'axe d'élément.

- 45 7. Système de projection selon la revendication 6, dans lequel le profil d'épaisseur présente une valeur constante le long d'un rayon qui est orienté perpendiculairement à l'axe d'élément et suivant un angle  $\theta$  par rapport à l'axe de référence.

8. Système de projection selon la revendication 6 ou 7, dans lequel une section d'azimut  $d(r=\text{const.}, \theta)$  du profil d'épaisseur  $d(r, \theta)$  dans une plage d'angles d'azimut de  $10^\circ < \theta < 350^\circ$  et à une distance constante  $r$  de l'axe d'élément est une fonction linéaire de l'angle d'azimut  $\theta$ , où cette section d'azimut présente une pente  $m$  se conformant

50 approximativement à l'expression  $|m| = \frac{180^\circ}{\alpha \pi r}$ ,  $\alpha$  représentant la rotation spécifique du cristal optiquement actif.

- 55 9. Système de projection selon la revendication 8, dans lequel la section d'azimut  $d(r=\text{const.}, \theta)$  présente une augmentation sensiblement similaire à un saut de  $360^\circ/\alpha$  à l'angle d'azimut  $\theta=0^\circ$ .

10. Système de projection selon la revendication 6 ou 7, dans lequel une section d'azimut  $d(r=\text{const.}, \theta)$  du profil d'épaisseur  $d(r, \theta)$  dans une plage d'angles d'azimut de  $10^\circ < \theta < 170^\circ$  et  $190^\circ < \theta < 350^\circ$  à une distance constante  $r$  de

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l'axe d'élément est une fonction linéaire de l'angle d'azimut  $\theta$ , où cette section d'azimut présente une pente  $m$  se conformant approximativement à l'expression  $|m| = \frac{180^\circ}{\alpha \pi r}$ ,  $\alpha$  représentant la rotation spécifique du cristal optiquement actif.

- 5
11. Système de projection selon la revendication 10, dans lequel la section d'azimut  $d(r=\text{const.}, \theta)$  présente une augmentation sensiblement similaire à un saut de  $180^\circ/\alpha$  aux angles d'azimut  $\theta=0^\circ$  et  $\theta=180^\circ$ .
- 10
12. Système de projection selon la revendication 6 ou 7, dans lequel une section d'azimut  $d(r=\text{const.}, \theta)$  du profil d'épaisseur  $d(r, \theta)$  à une distance constante  $r$  de l'axe d'élément et dans une première plage d'angles d'azimut de  $10^\circ < \theta < 170^\circ$  est une fonction linéaire de l'angle d'azimut  $\theta$  présentant une première pente  $m$ , alors que dans une deuxième plage d'angles d'azimut de  $190^\circ < \theta < 350^\circ$ , la section d'azimut est une fonction linéaire de l'angle d'azimut  $\theta$  présentant une deuxième pente  $n$ , où les pentes  $m$  et  $n$  ont la même amplitude absolue mais des signes opposés,
- 15
- et où l'amplitude des pentes  $m$  et  $n$  est conforme à l'expression  $|m| = |n| = \frac{180^\circ}{\alpha \pi r}$ ,  $a$  représentant la rotation spécifique du cristal optiquement actif.
- 20
13. Système de projection selon l'une des revendications 1 à 7, dans lequel l'élément optique de modulation de la polarisation est constitué de ou comprend au moins deux parties parallèles planes d'épaisseur différente ou d'épaisseur effective optique différente.
- 25
14. Système de projection selon la revendication 13, dans lequel les parties sont configurées sous forme de secteurs d'un cercle ou sous forme d'éléments échantillonnés de forme hexagonale, carrée, rectangulaire ou trapézoïdale et/ou comprennent au moins une cuvette comprenant un liquide optiquement actif ou optiquement inactif.
- 30
15. Système de projection selon la revendication 13 ou 14, dans lequel une paire de premières parties parallèles dans un plan sont agencées sur les côtés opposés d'un axe d'élément central de l'élément optique de modulation de la polarisation et dans lequel une paire de deuxièmes parties parallèles dans un plan sont agencées sur les côtés opposés de l'axe d'élément et déplacées de façon circonférentielle autour de l'axe d'élément par rapport aux premières parties parallèles dans un plan, où chacune des premières parties présente une épaisseur ou une épaisseur effective optique qui est différente d'une épaisseur ou d'une épaisseur effective optique de chacune des deuxièmes parties.
- 35
16. Système de projection selon la revendication 15, dans lequel un plan d'oscillation de la lumière polarisée linéairement traversante est tourné d'un premier angle de rotation  $\beta_1$  dans au moins une des premières parties parallèles dans un plan et d'un deuxième angle de rotation  $\beta_2$  dans au moins une des deuxièmes parties parallèles dans un plan, de telle sorte que  $\beta_1$  et  $\beta_2$  sont approximativement conformes à l'expression  $|\beta_2 - \beta_1| = (2n+1) \cdot 90^\circ$ ,  $n$  représentant un nombre entier.
- 40
17. Système de projection selon la revendication 16, dans lequel  $\beta_1$  et  $\beta_2$  sont approximativement conformes aux expressions  $\beta_1 = 90^\circ + p \cdot 180^\circ$ ,  $p$  représentant un nombre entier, et  $\beta_2 = q \cdot 180^\circ$ ,  $q$  représentant un nombre entier autre que zéro.
- 45
18. Système de projection selon l'une quelconque des revendications 15 à 17, dans lequel la paire de deuxièmes parties parallèles dans un plan est déplacée de façon circonférentielle autour de l'axe d'élément par rapport à la paire des premières parties parallèles dans un plan d'approximativement  $90^\circ$ .
- 50
19. Système de projection selon l'une quelconque des revendications 15 à 18, dans lequel la paire de premières parties parallèles dans un plan et la paire de deuxièmes parties parallèles dans un plan sont agencées sur les côtés opposés d'une ouverture centrale ou d'un obscurcissement central de l'élément optique de modulation de la polarisation.
- 55
20. Système de projection selon l'une quelconque des revendications 15 à 19, dans lequel les parties adjacentes des première et deuxième paires sont écartées l'une de l'autre par des zones qui sont opaques ou qui ne sont pas optiquement actives vis-à-vis d'une lumière polarisée linéairement qui pénètre dans l'élément optique de modulation de la polarisation.
21. Système de projection selon l'une quelconque des revendications 15 à 20, dans lequel les parties des première et

deuxième paires sont maintenues ensemble par une pièce de fixation.

- 5
22. Système de projection selon la revendication 21, dans lequel la pièce de fixation est opaque ou n'est pas optiquement active vis-à-vis d'une lumière polarisée linéairement qui pénètre dans l'élément optique de modulation de la polarisation.
- 10
23. Système de projection selon la revendication 21 ou 22, dans lequel la pièce de montage présente une forme de roue à rayons sensiblement.
- 15
24. Système de projection selon l'une quelconque des revendications 13 à 23, comprenant un premier groupe de parties sensiblement parallèles et planes où un plan d'oscillation d'une lumière polarisée linéairement traversante est tourné d'un premier angle de rotation  $\beta_1$  et un deuxième groupe de parties sensiblement parallèles et planes où un plan d'oscillation d'une lumière polarisée linéairement traversante est tourné d'un deuxième angle de rotation, de telle sorte que  $\beta_1$  et  $\beta_2$  sont approximativement conformes à l'expression  $|\beta_2 - \beta_1| = (2n+1) \cdot 90^\circ$ , n représentant un nombre entier.
- 20
25. système de projection selon la revendication 24, dans lequel  $\beta_1$  et  $\beta_2$  sont approximativement conformes aux expressions  $\beta_1 = 90^\circ + p \cdot 180^\circ$ , p représentant un nombre entier, et  $\beta_2 = q \cdot 180^\circ$ , q représentant un nombre entier autre que zéro.
- 25
26. Système de projection selon l'une quelconque des revendications 1 à 7, dans lequel le profil d'épaisseur ou le profil d'épaisseur optique effective présente une forme continue.
- 30
27. Système de projection selon l'une quelconque des revendications précédentes, comprenant en outre un diamètre d'élément D et une épaisseur minimale  $d_{\min}$ , où l'épaisseur minimale  $d_{\min}$  est au moins égale à 0,002 fois le diamètre d'élément D.
- 35
28. Système de projection selon l'une quelconque des revendications précédentes, dans lequel le profil d'épaisseur présente une épaisseur minimale  $d_{\min} = N \cdot \frac{90^\circ}{\alpha}$ ,  $\alpha$  représentant la rotation spécifique du cristal optiquement actif et N représentant un nombre entier positif.
- 40
29. Système de projection selon l'une quelconque des revendications précédentes, dans lequel l'élément optique de modulation de la polarisation comporte une ouverture centrale ou un obscurcissement central.
- 45
30. Système de projection selon l'une quelconque des revendications précédentes, dans lequel l'élément optique de modulation de la polarisation transforme un faisceau de lumière entrant ayant une première distribution de polarisation en un faisceau de lumière sortant ayant une deuxième distribution de polarisation, dans lequel le faisceau de lumière entrant est constitué d'une multitude de rayons lumineux ayant une distribution d'angle par rapport à l'axe optique du cristal optiquement actif, et dans lequel la distribution d'angle présente un angle d'incidence maximum ne dépassant pas 100 mrad.
- 50
31. Système de projection selon l'une quelconque des revendications précédentes, dans lequel un agencement optique ayant ledit élément optique de modulation de la polarisation est organisé dans le système d'éclairage, dans lequel l'agencement optique est configuré de telle sorte qu'au moins un autre élément optique de modulation de la polarisation peut être placé dans le trajet de la lumière.
- 55
32. Système de projection selon la revendication 31, dans lequel l'autre élément optique de modulation de la polarisation comprend un élément optique de modulation de la polarisation qui a un profil d'épaisseur ou comprend un profil d'épaisseur et est constitué de ou comprend un cristal optiquement actif ayant un axe optique, où le profil d'épaisseur, mesuré dans la direction de l'axe optique dudit cristal optiquement actif, est variable.
33. Système de projection selon la revendication 31, dans lequel l'autre élément optique de modulation de la polarisation comprend une plaque parallèle plane d'un cristal optiquement actif et/ou une cuvette ayant un liquide optiquement actif ou optiquement inactif.
34. Système de projection selon la revendication 31, dans lequel l'autre élément optique de modulation de la polarisation

comprend un rotateur constitué de deux plaques de demi-longueur d'onde qui sont entraînées en rotation de 45° l'une par rapport à l'autre.

- 5
35. Système de projection selon la revendication 31, dans lequel l'élément optique de modulation de la polarisation comporte un axe d'élément en référence auquel le profil d'épaisseur a une variation qui dépend uniquement d'un angle d'azimut  $\theta$ , où l'angle d'azimut  $\theta$  est mesuré à partir d'un axe de référence qui est orienté perpendiculairement à l'axe d'élément et coupe l'axe d'élément, dans lequel le profil d'épaisseur dans une première plage d'angles d'azimut de  $10^\circ < \theta < 170^\circ$  est une fonction linéaire de l'angle d'azimut  $\theta$  présentant une première pente  $m$ , alors que dans une deuxième plage d'angles d'azimut de  $190^\circ < \theta < 350^\circ$ , la section d'azimut est une fonction linéaire de l'angle d'azimut  $\theta$  présentant une deuxième pente  $n$ , où les pentes  $m$  et  $n$  ont la même amplitude absolue mais des signes opposés, et où l'autre élément optique de modulation de la polarisation comprend une plaque parallèle plane qui est configurée sous forme d'une plaque de demi-longueur d'onde pour un demi-espace qui couvre une plage d'angles d'azimut de  $180^\circ$ .
- 10
- 15
36. Système de projection selon la revendication 31, dans lequel l'autre élément optique de modulation de la polarisation provoque une rotation à  $90^\circ$  du plan d'oscillation d'un rayon lumineux polarisé linéairement traversant ledit agencement optique.
- 20
37. Système de projection selon l'une quelconque des revendications 31 à 36, dans lequel une plaque de compensation est agencée dans le trajet de la lumière du système optique, ladite plaque de compensation présentant un profil d'épaisseur configuré pour compenser globalement les écarts d'angles du rayonnement transmis qui sont provoqués par l'élément optique de modulation de la polarisation.
- 25
38. Système de projection selon l'une quelconque des revendications précédentes, dans lequel un milieu d'immersion présentant un indice de réfraction différent de l'air est présent entre le substrat et un élément optique à proximité immédiate du substrat.
- 30
39. Procédé de fabrication de composants à semi-conducteurs microstructurés, comprenant une étape d'utilisation d'un système de projection conforme à l'une des revendications précédentes.

35

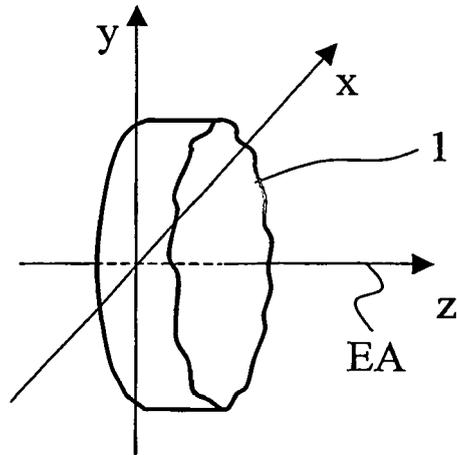
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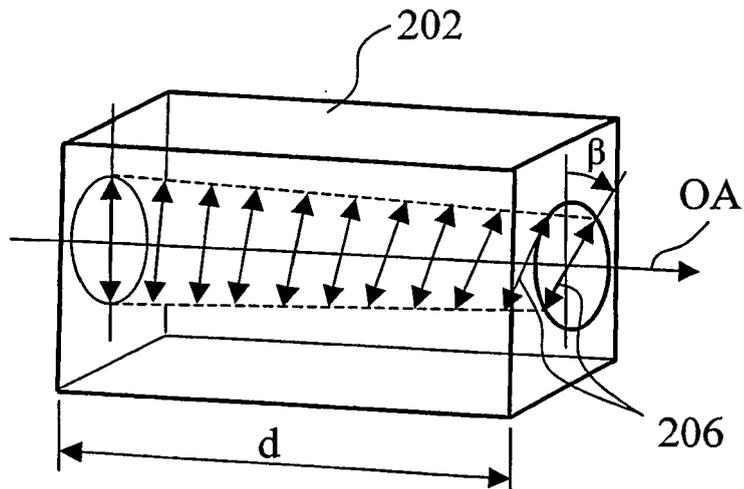
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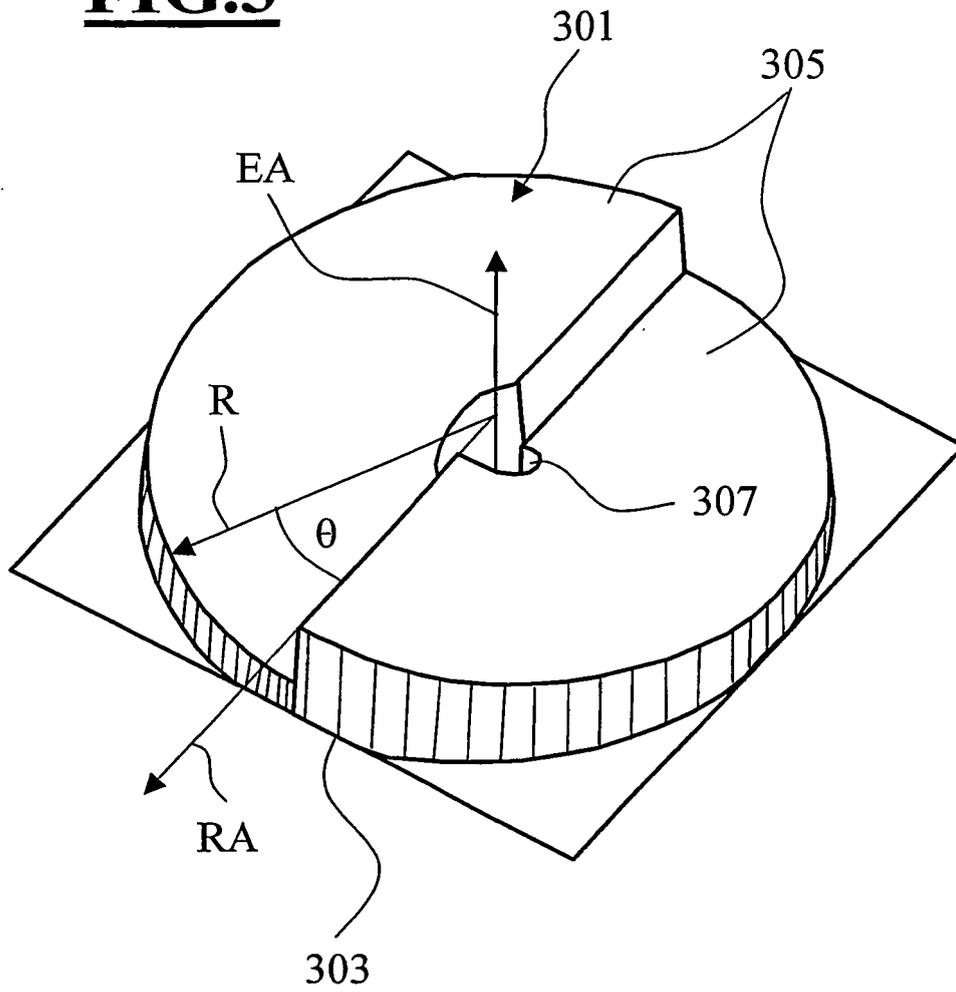
**FIG.1**



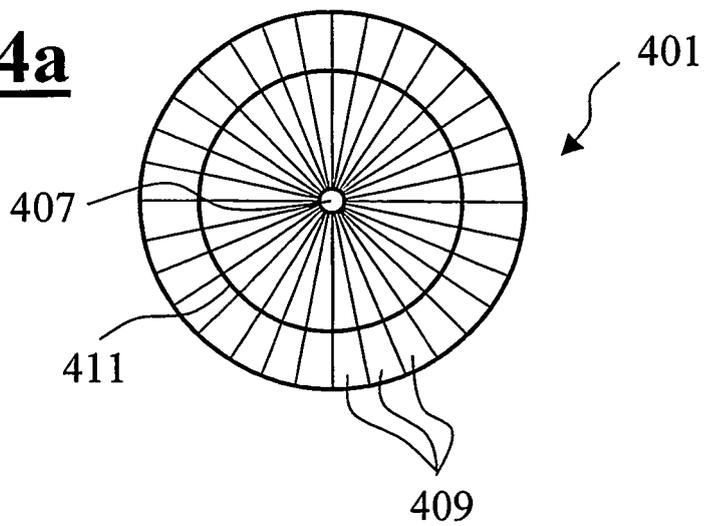
**FIG.2**

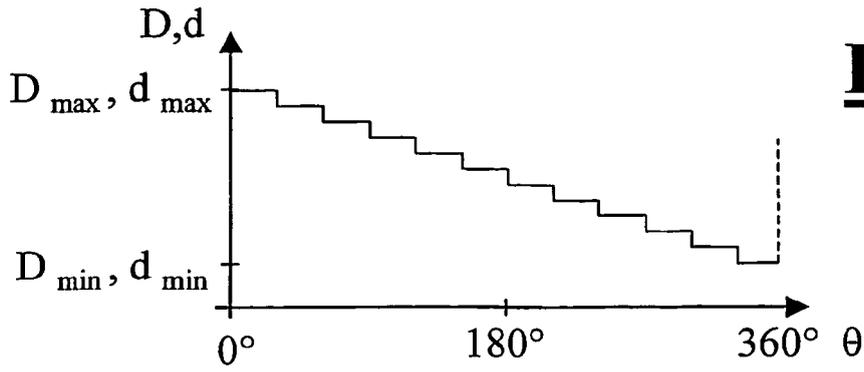


**FIG.3**

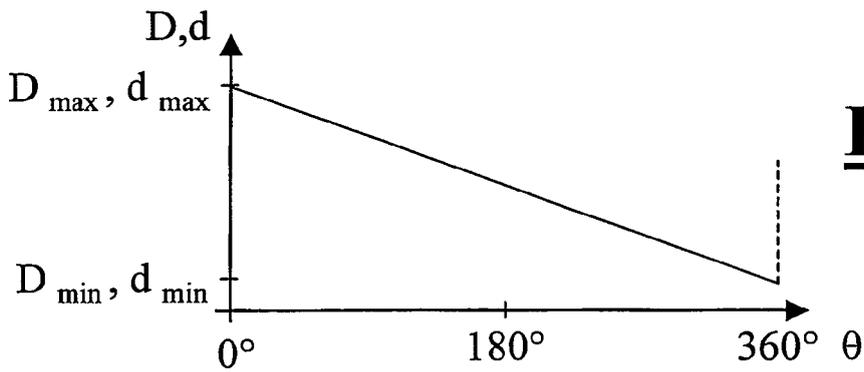


**FIG.4a**

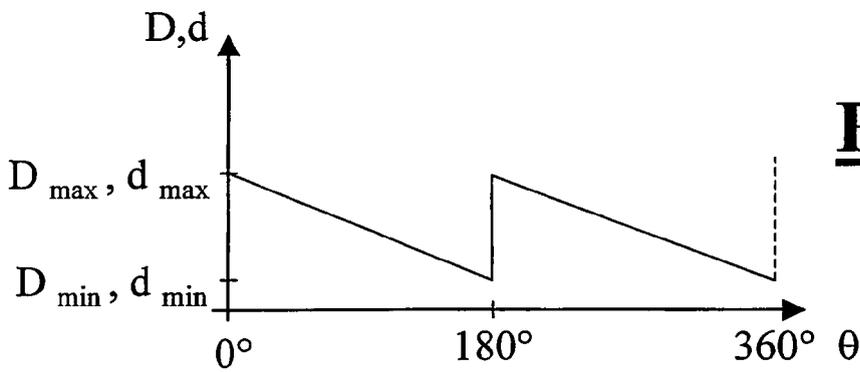




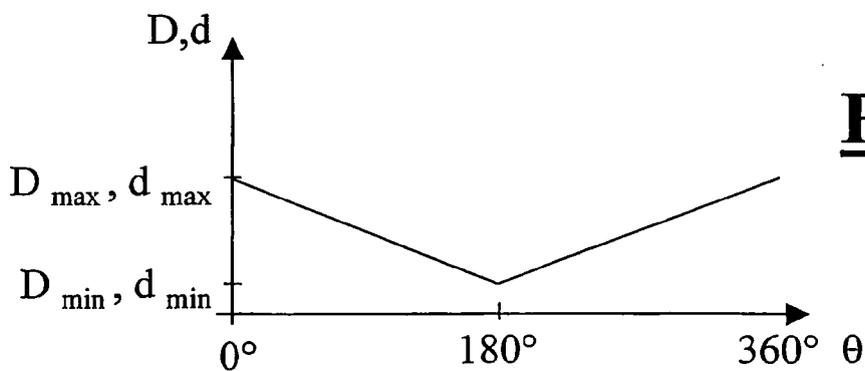
**FIG.4b**



**FIG.4c**

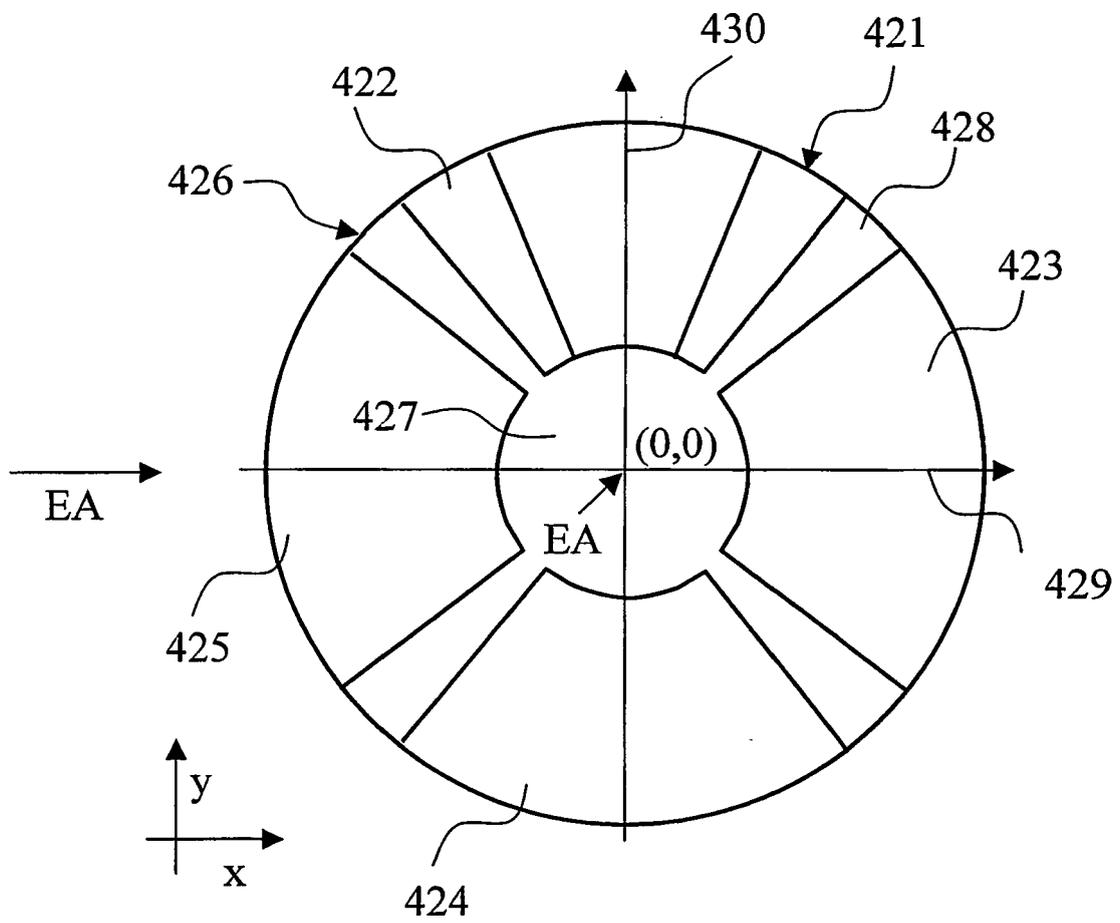


**FIG.4d**

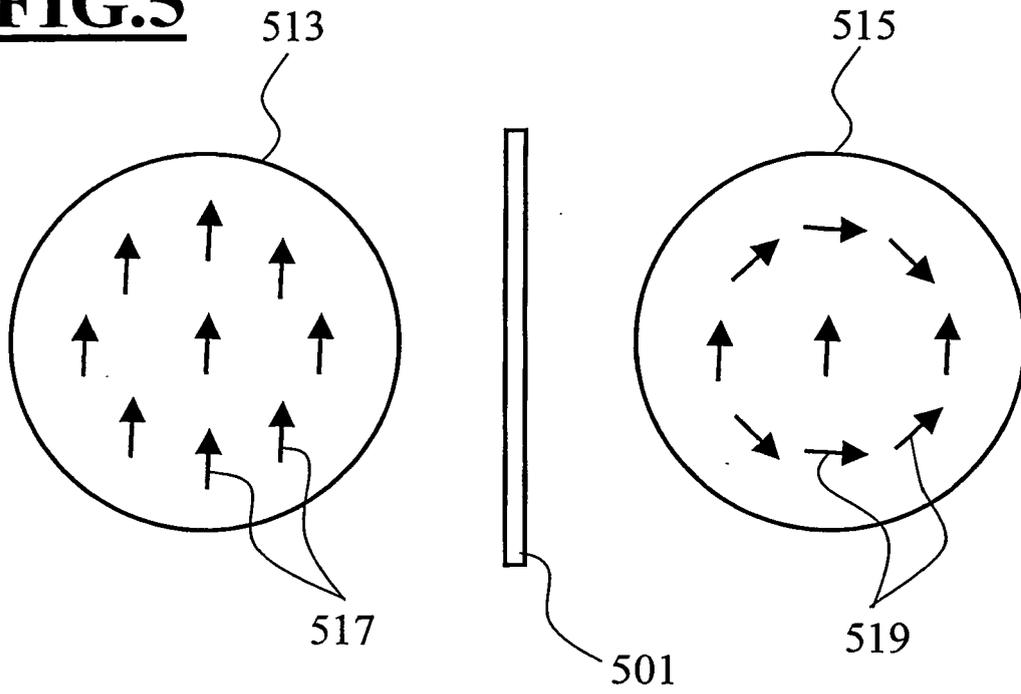


**FIG.4e**

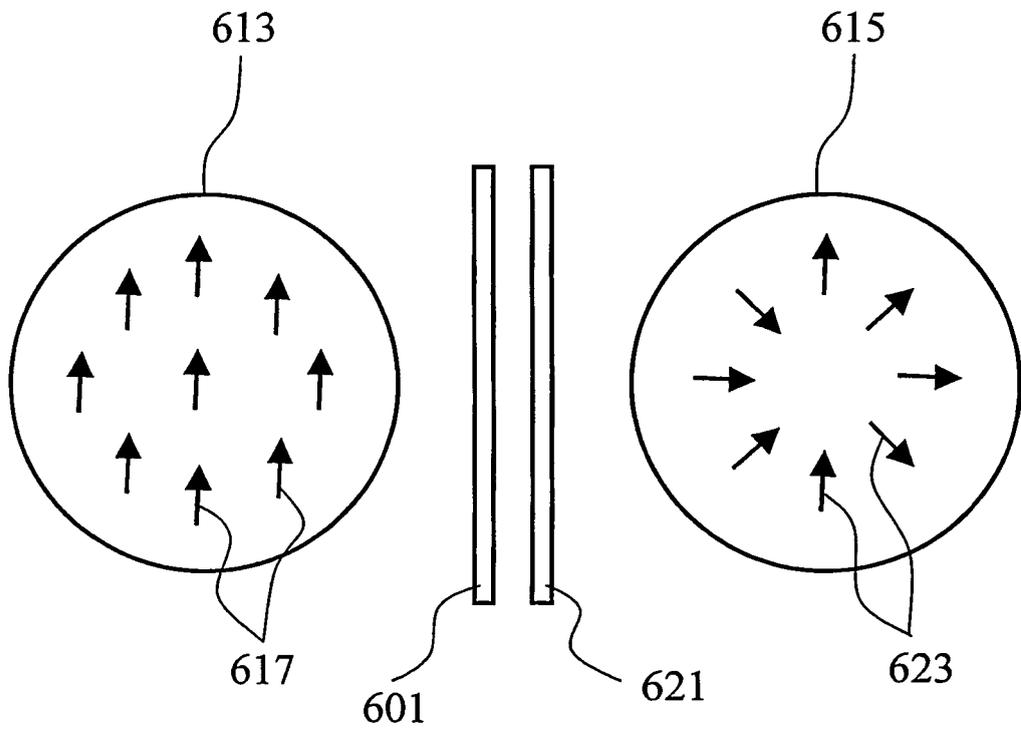
**FIG.4f**



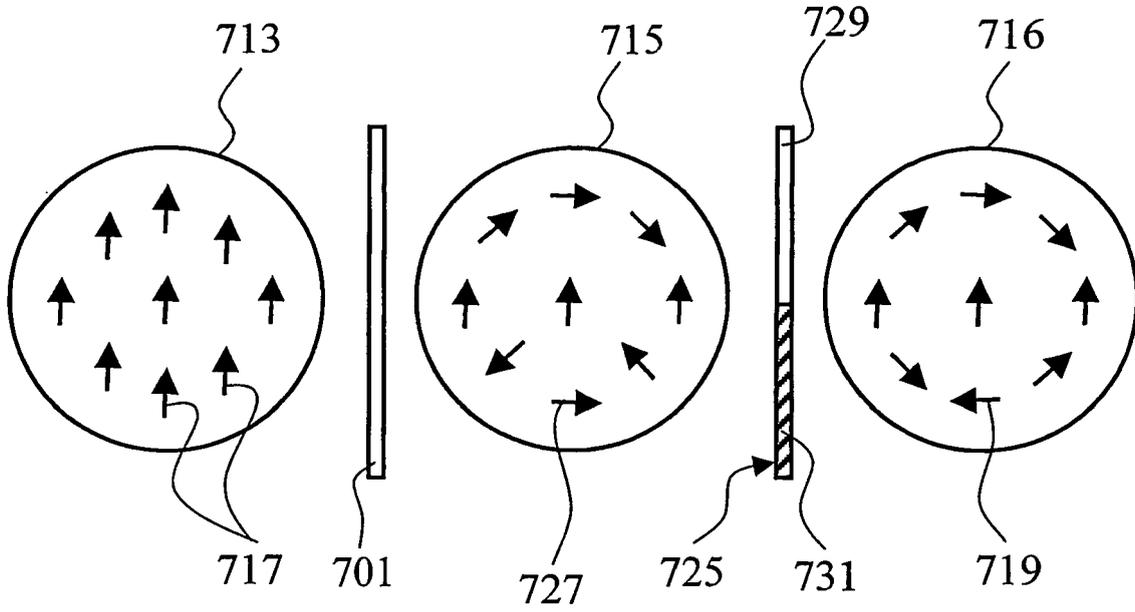
**FIG.5**



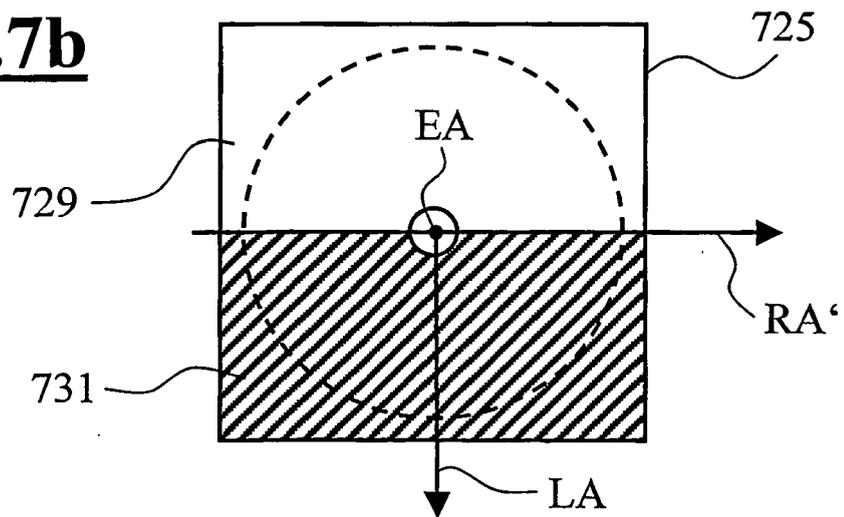
**FIG.6**



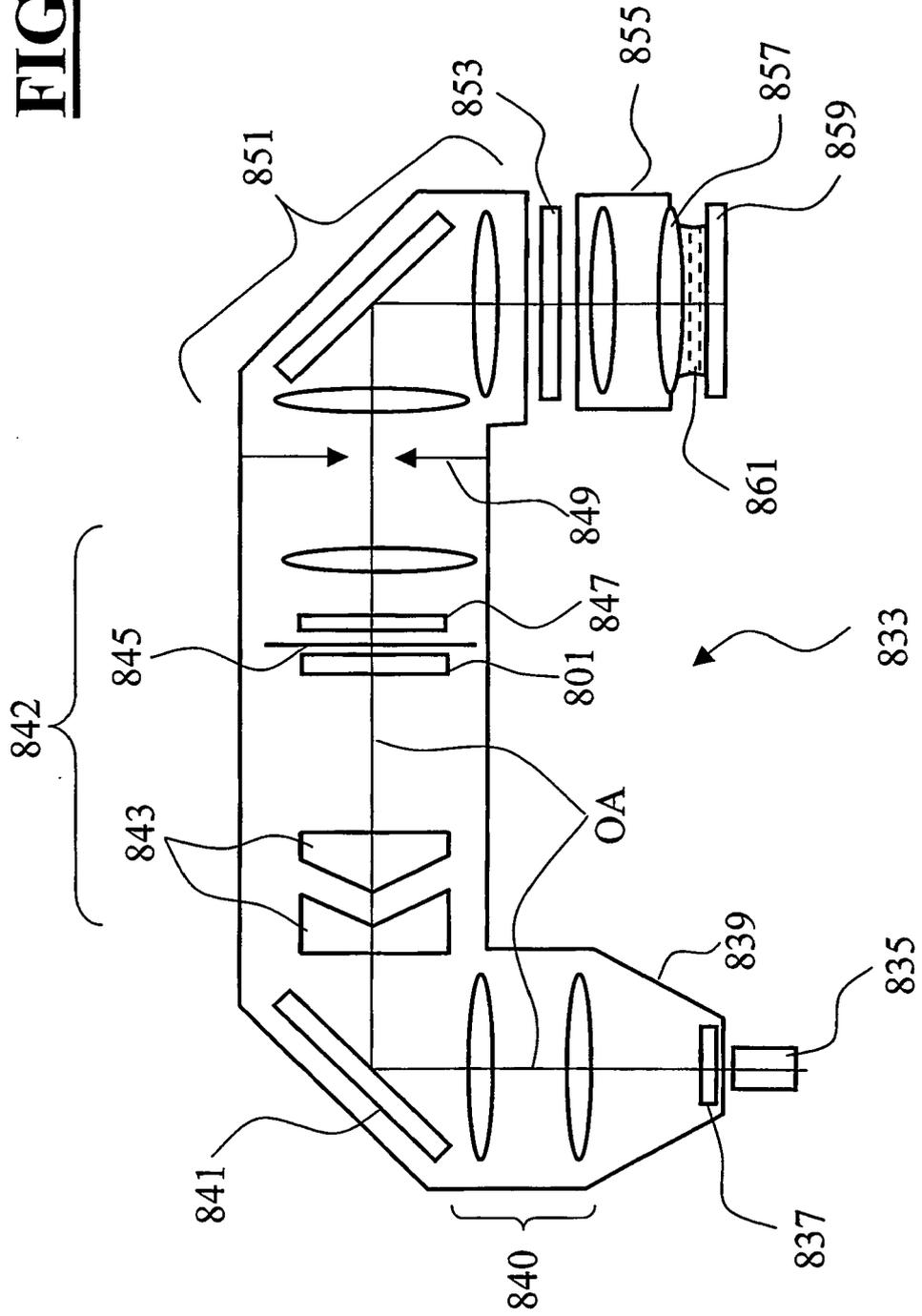
**FIG. 7a**



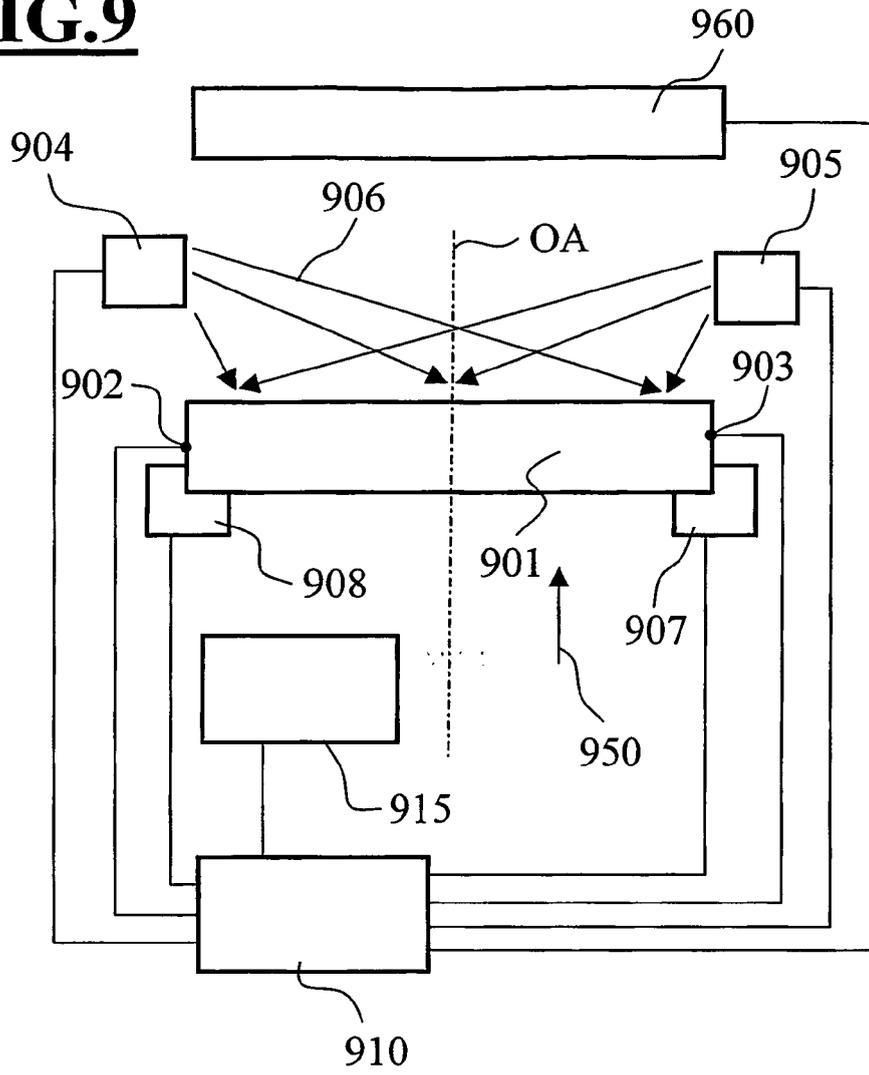
**FIG. 7b**



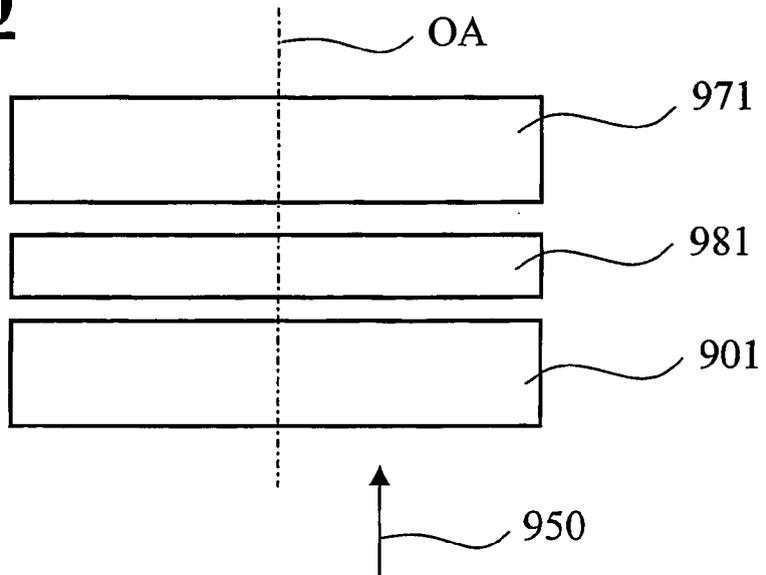
**FIG. 8**



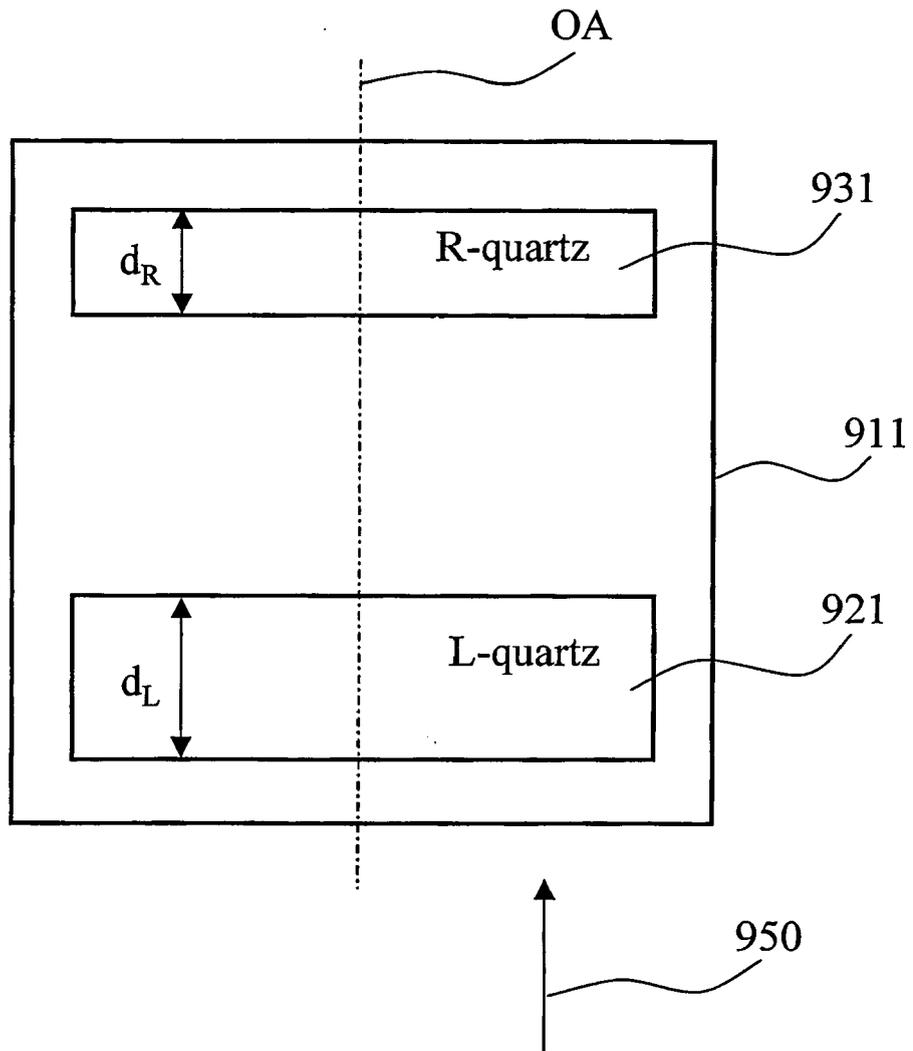
**FIG.9**



**FIG.10**



**FIG.11**



**REFERENCES CITED IN THE DESCRIPTION**

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**Patent documents cited in the description**

- US 6191880 B1 [0007]
- DE 19807120 A1 [0008]
- GB 856621 A [0009]
- US 2003095241 A1 [0009]
- DE 19529563 [0081]
- US 6258433 B [0081]